

Transparent Conductors

Part II

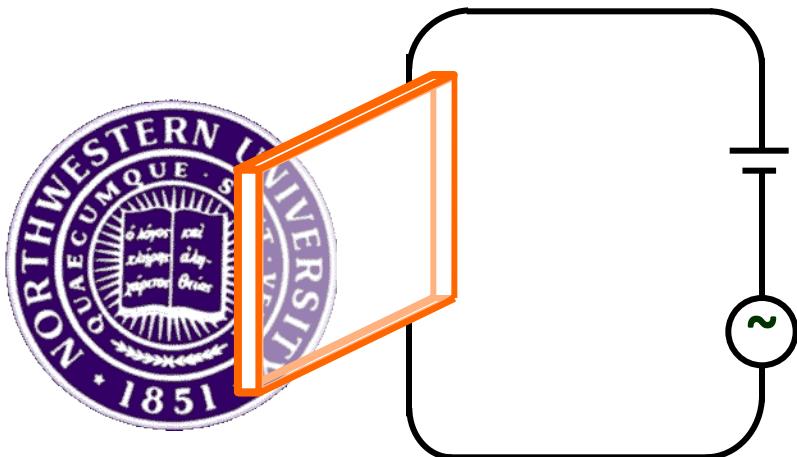
Prof. Tom Mason
Northwestern University
Materials Science & Engineering

Conclusions

- With the exception of ZnO, the best TCOs are high octahedral site density crystal structures
- They are n-type only
- The “basis” cations are In, Sn, Zn, Cd and Ga
- Their defect chemistries can be complicated (not just oxygen vacancies)
- Phase diagrams play an important role
- If you can make a comparable p-type TCO...

An Introduction to TCOs

Transparency
(> 80% through visible spectrum for typical 1 μm thin film)



Conductivity (> 10^3 S/cm)

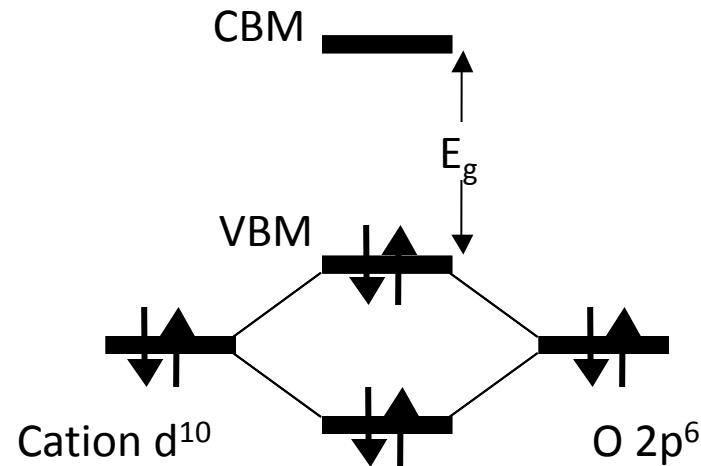
- What About p-Type TCOs
- The Importance of Work Functions
- The What and How of Work Functions
- Surface Science Definitions
- Work Function “Myths”
- Manipulating Work Functions
- Motivation for New TCOs
- Amorphous TCOs
- What the Future Holds

What About p-Type TCOs?

The Strategy of Kawazoe et al.

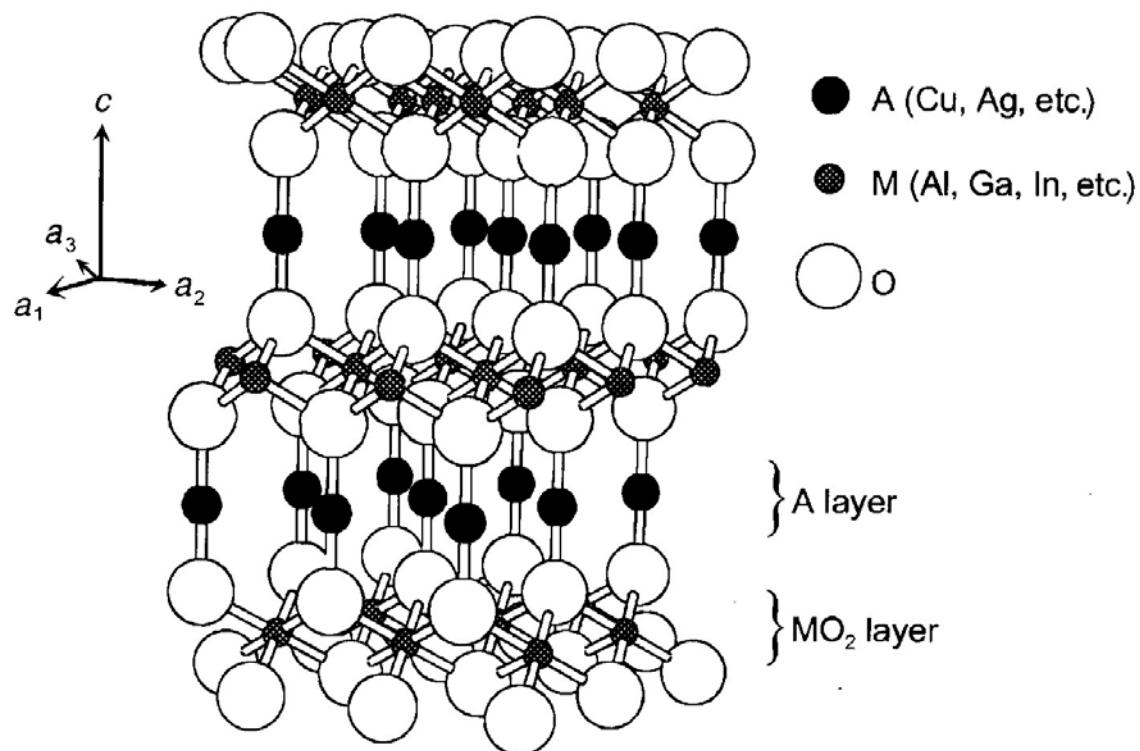
- Delocalize O-2p levels at the VBM through enhanced covalency
 - Quasi-tetrahedral coordination of oxygen by cations
 - Linear coordination of cations
- Chose d¹⁰ cations with energy levels close to that of O-2p

p-type TCOs



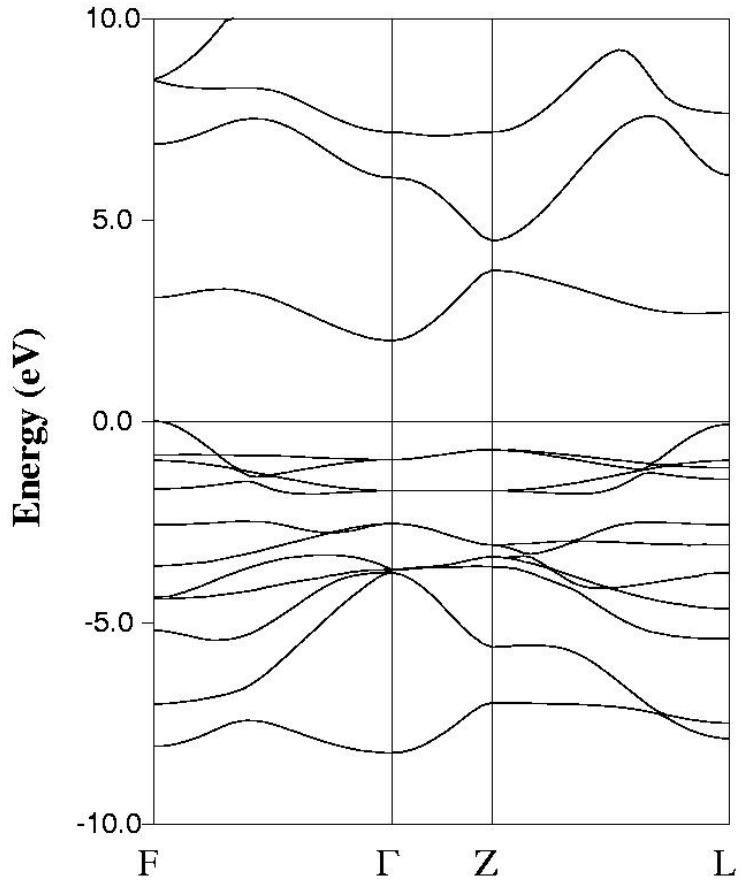
Linear cation TCO family

"delafoelite" AMO_2



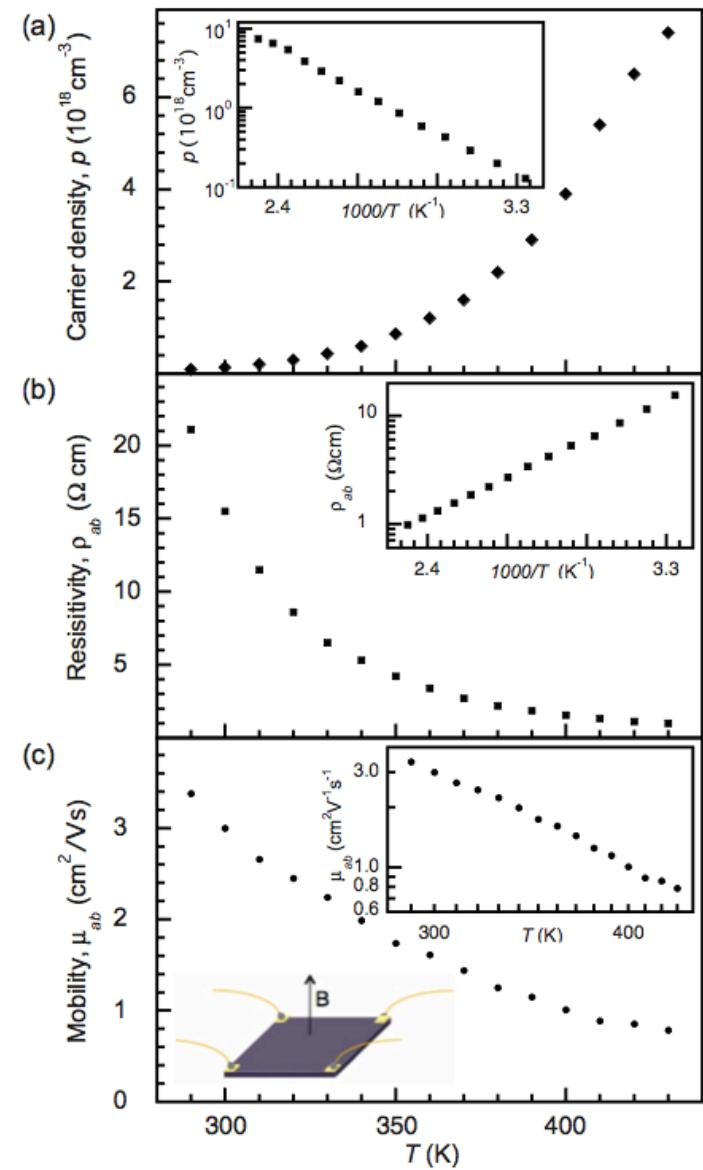
- Alternating layers of octahedra and Cu in linear coordination
- Two stacking sequences: rhombohedral and hexagonal
- p-type!

Band structure of CuAlO₂



CuAlO₂ Single Crystal Electrical Results

- Band Conductor
- Relatively low, anisotropic mobilities
 - *ab*-plane: $3.0 \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$
 - *c*-direction: $0.12 \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1}$
- Tough to dope!



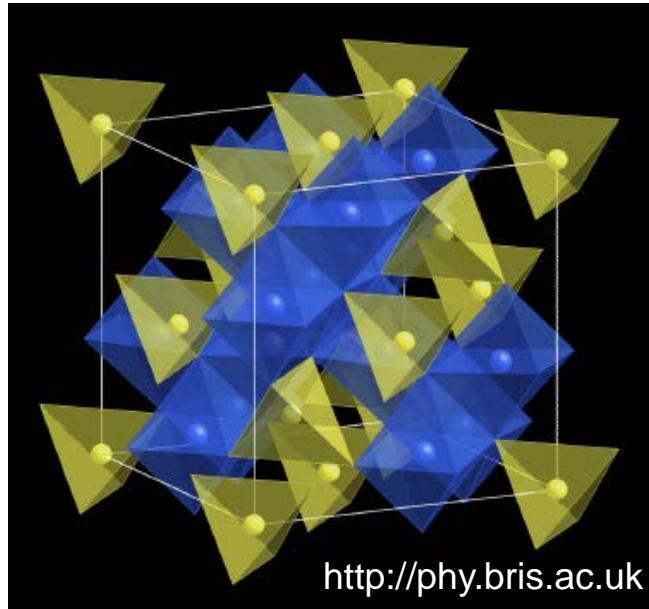
Review of literature data for delafossites

	σ (S/cm)	%T (visible) (film thickness)	E_g (eV)
CuYO ₂ :Ca ⁽¹⁾	1.0	40-50 (250 nm)	3.5
CuScO ₂ ⁽²⁾	15-30	40 (110 nm)	
CuGaO ₂ ⁽³⁾	6.3x10 ⁻²	80 (500 nm)	3.6
CuInO ₂ :Ca ⁽⁴⁾	2.8x10 ⁻³ (p)		3.9
CuInO ₂ :Sn	3.8x10 ⁻³ (n)		
CuAlO ₂ ⁽⁵⁾	16	32-52 (120 nm)	3.6

1. M. K. Jayaraj, et al. *Thin Solid Films.* **397**, 244 (2001).
2. N. Duan, et al. *Appl. Phys. Lett.* **77**(9), 1 (2000).
3. K. Ueda, et al. *J. Appl. Phys.* **89**(3), 1790 (2001).
4. H. Yanagi, et al. *Appl. Phys. Lett.* **78**(11), 1583 (2001).
5. Y. Wang, et al. *Chem. Vap. Deposition.* **6**(6), 285 (2000).

A New Approach: Non-d¹⁰ Cations

d^6 p-TCOs: Spinels



Yellow:

Tetrahedral (T_d)

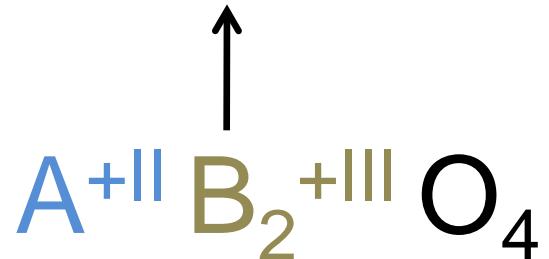
Blue:

Octahedral (O_h)

Vertices of each polyhedron are oxygen anions.

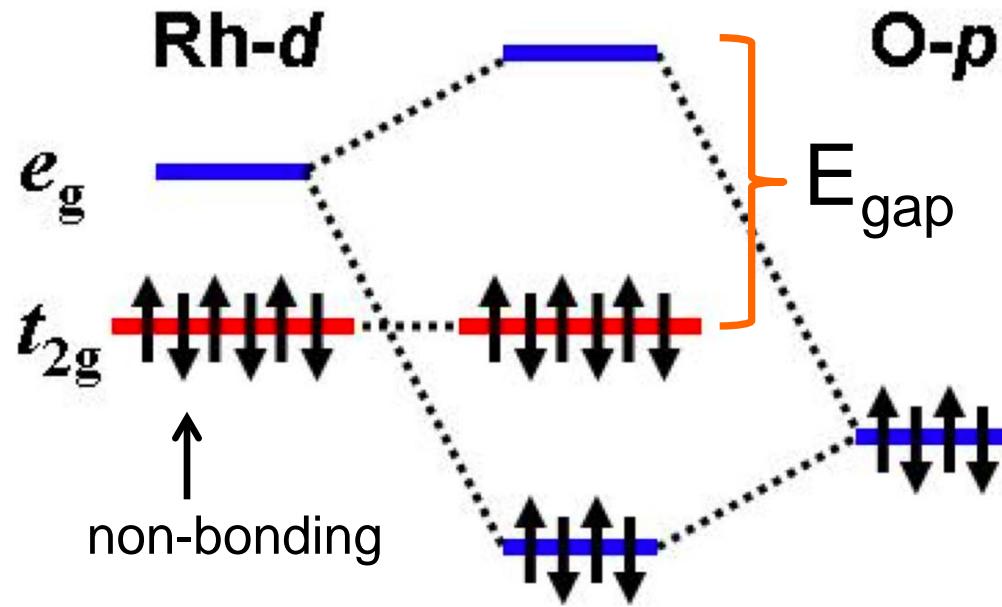
Normal II-III Spinels:

O_h site (e.g., Rh, Cr, Co)



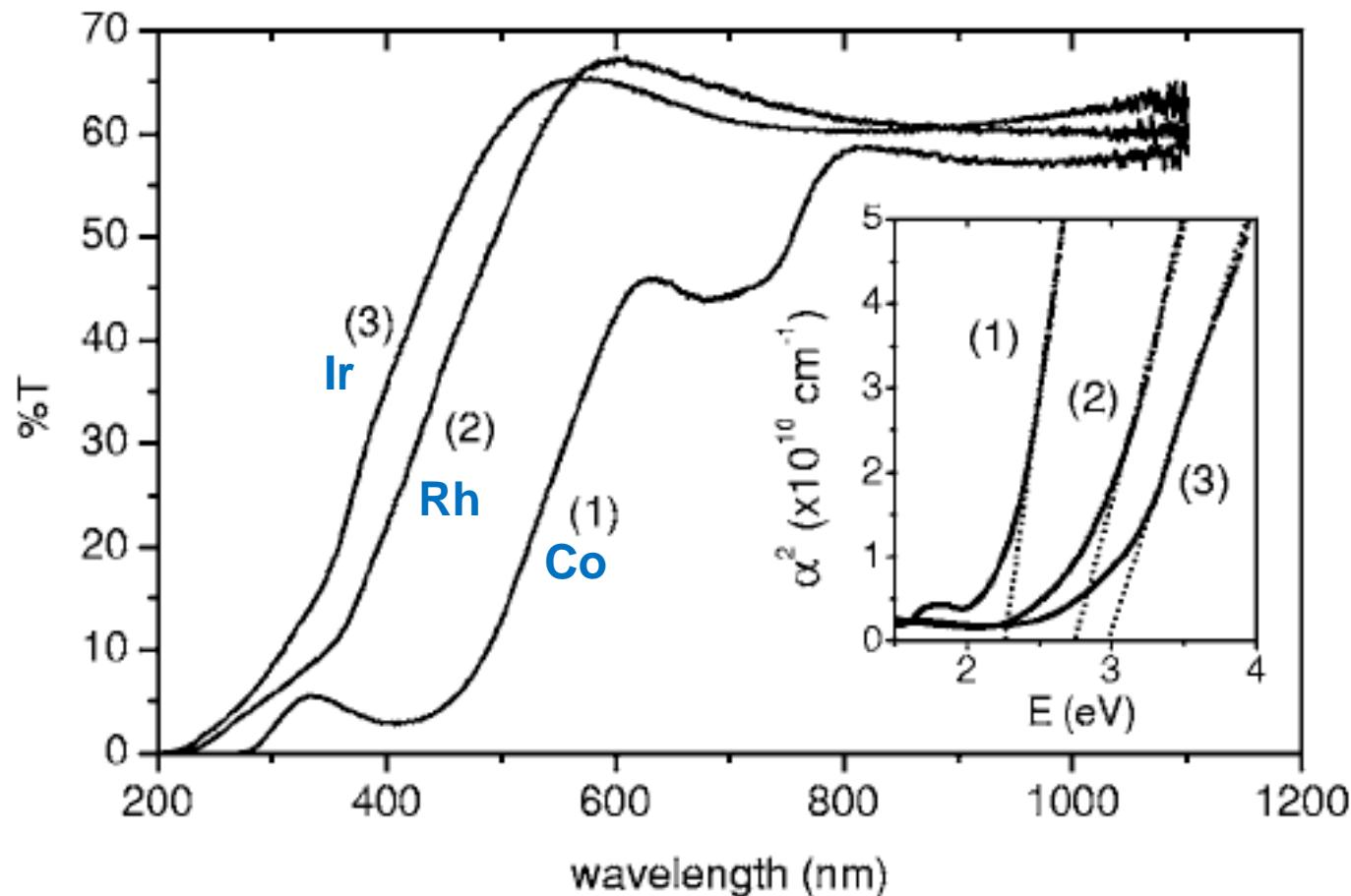
T_d site (e.g., Zn, Mg, Mn)

d^6 p-TCOs: Spinels



Crystal field splitting gives rise to transparency.

Transmission Data for ZnM_2O_4 (M = Ir, Rh, Co)



Electrical Data for d⁶ Spinels

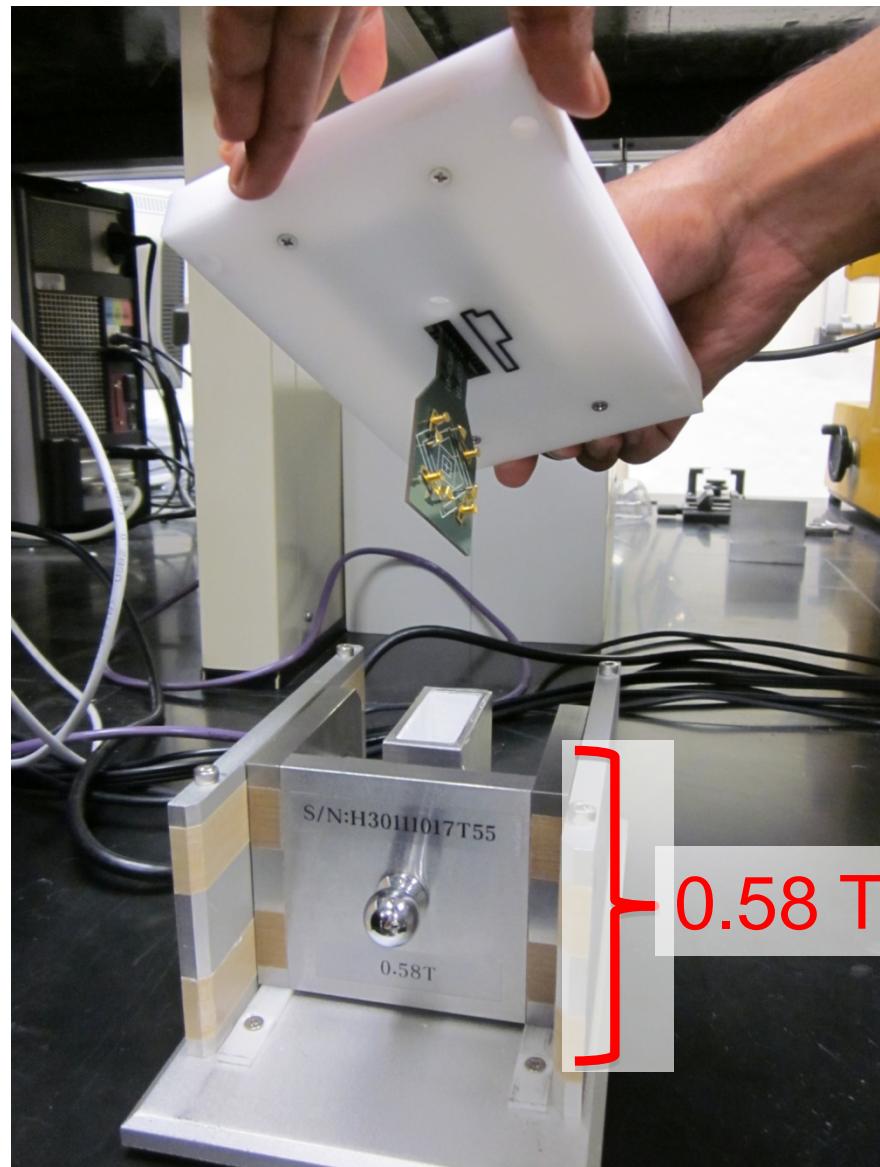
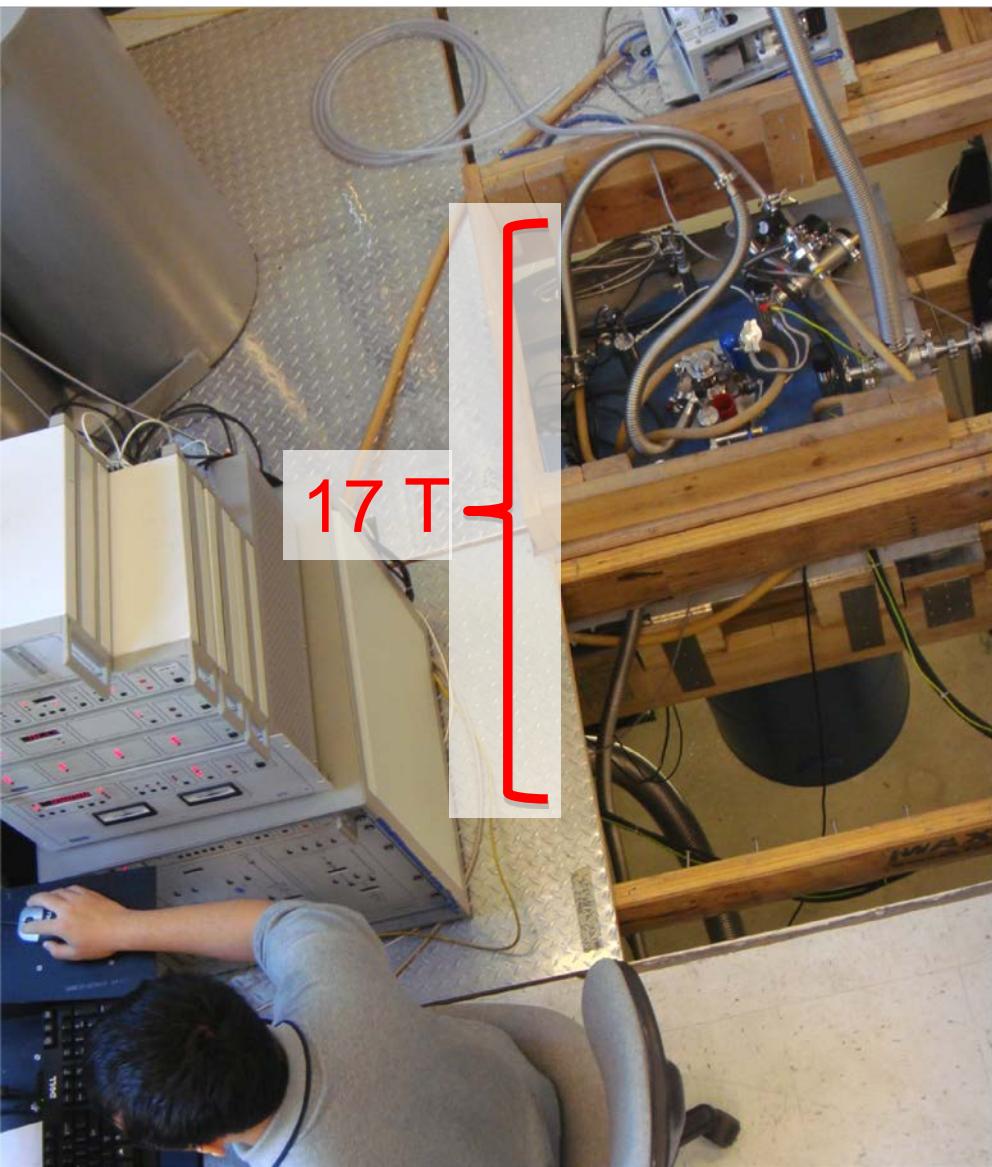
Composition	σ (S/cm)	E_g
ZnIr ₂ O ₄	3.39	2.97
ZnRh ₂ O ₄ ⁽¹⁾	2.75	2.74
ZnCo ₂ O ₄ ⁽¹⁾	0.39	2.26
ZnCo ₂ O ₄ :Mg ⁽²⁾ (bulk)	0.9	

Low conductivities attributed to small hole mobilities!

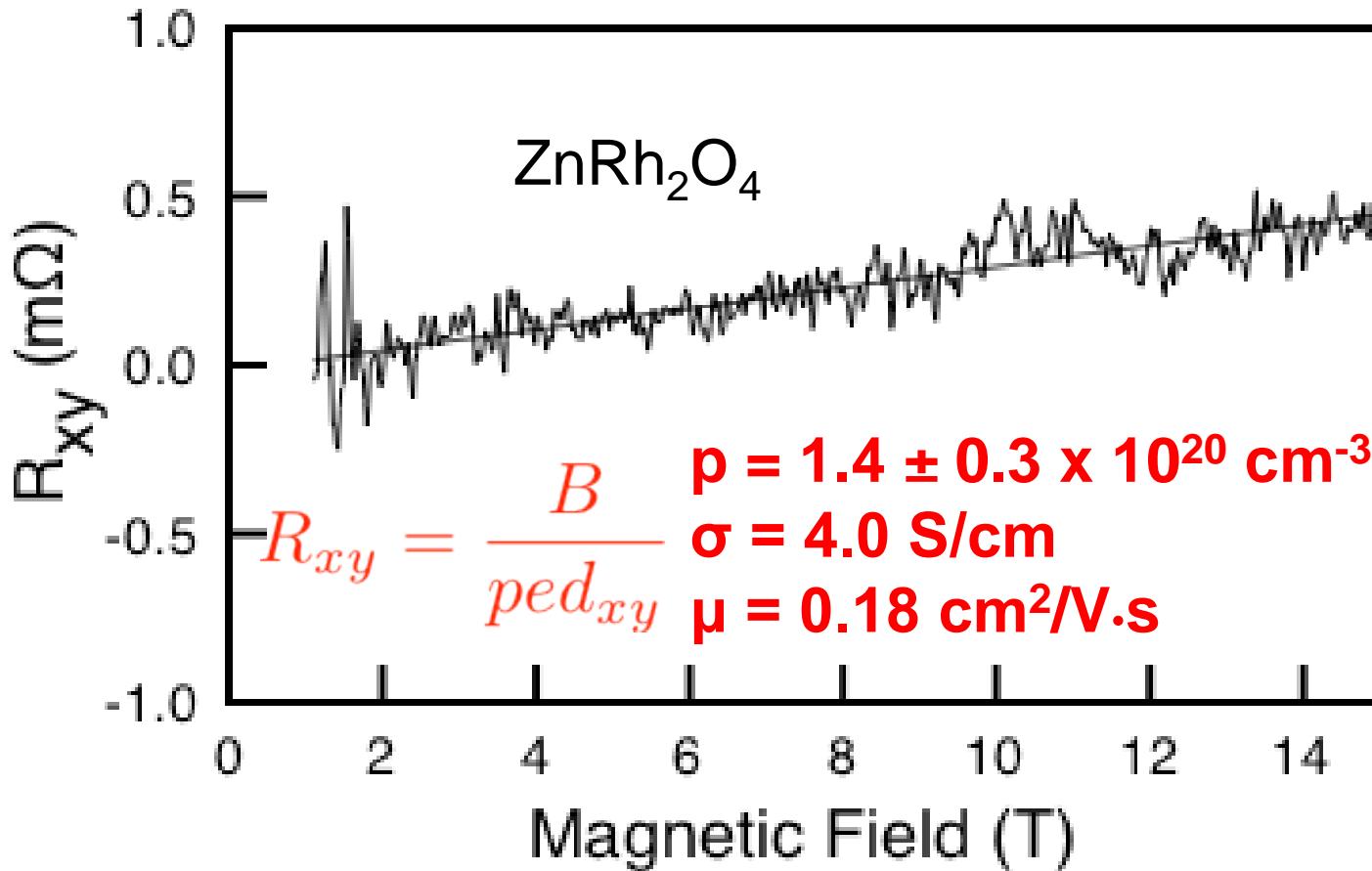
(1) M. Dekkers *et al.*, Appl Phys. Lett. **90**, 021903, (2007).

(2) J. Perkins *et al.*, Phys. Rev. B. **84**, 205207, (2011).

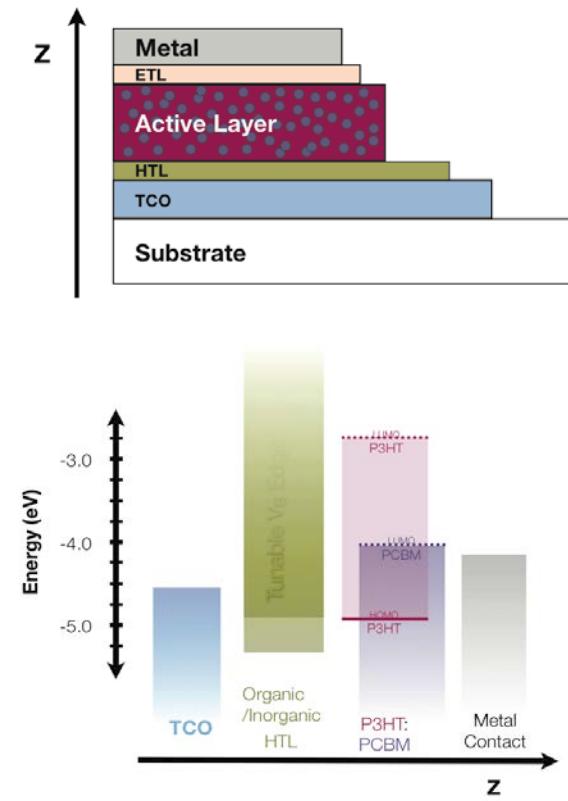
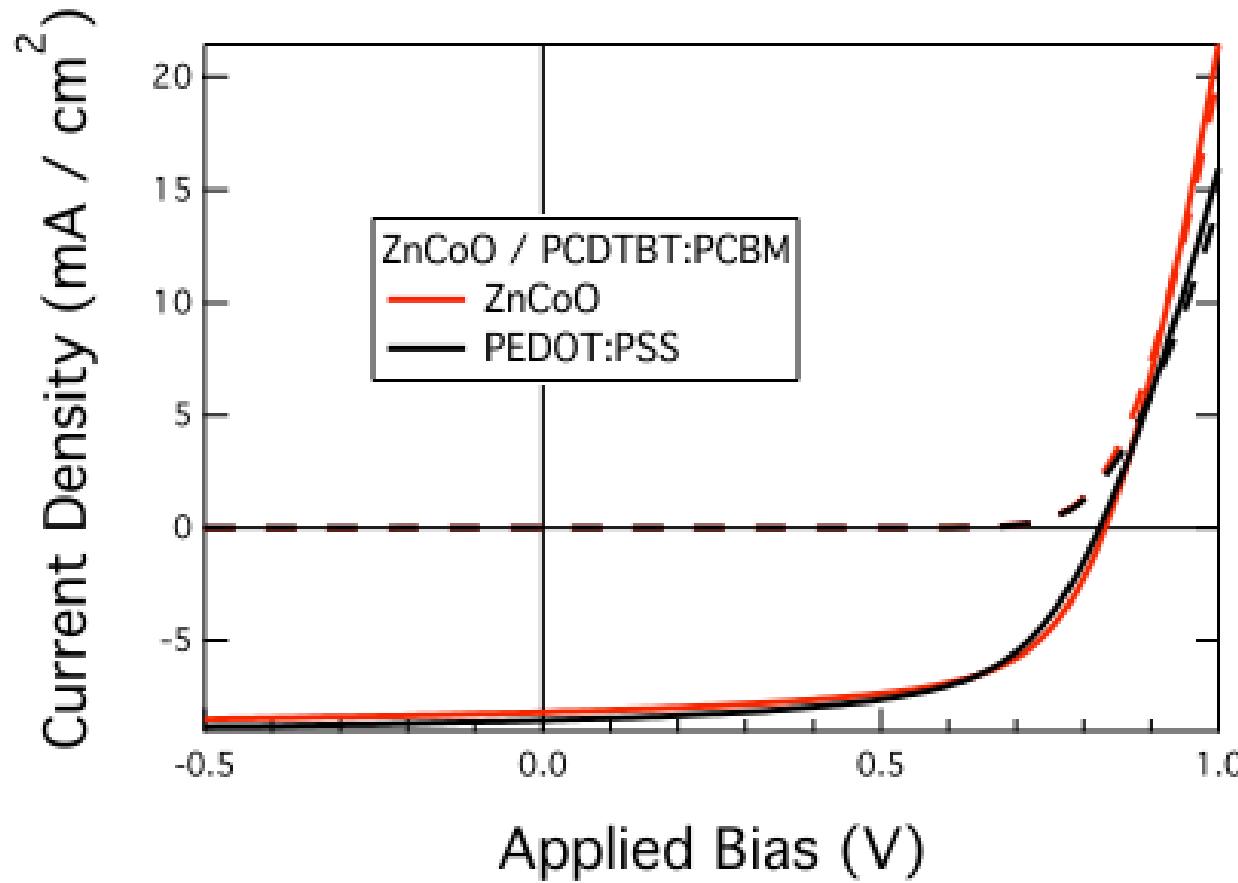
Hall Effect: 17 T and 0.58 T



Hall mobility at room temperature



Zn-Co-O is a Good Hole Transport Layer (HTL) for OPV



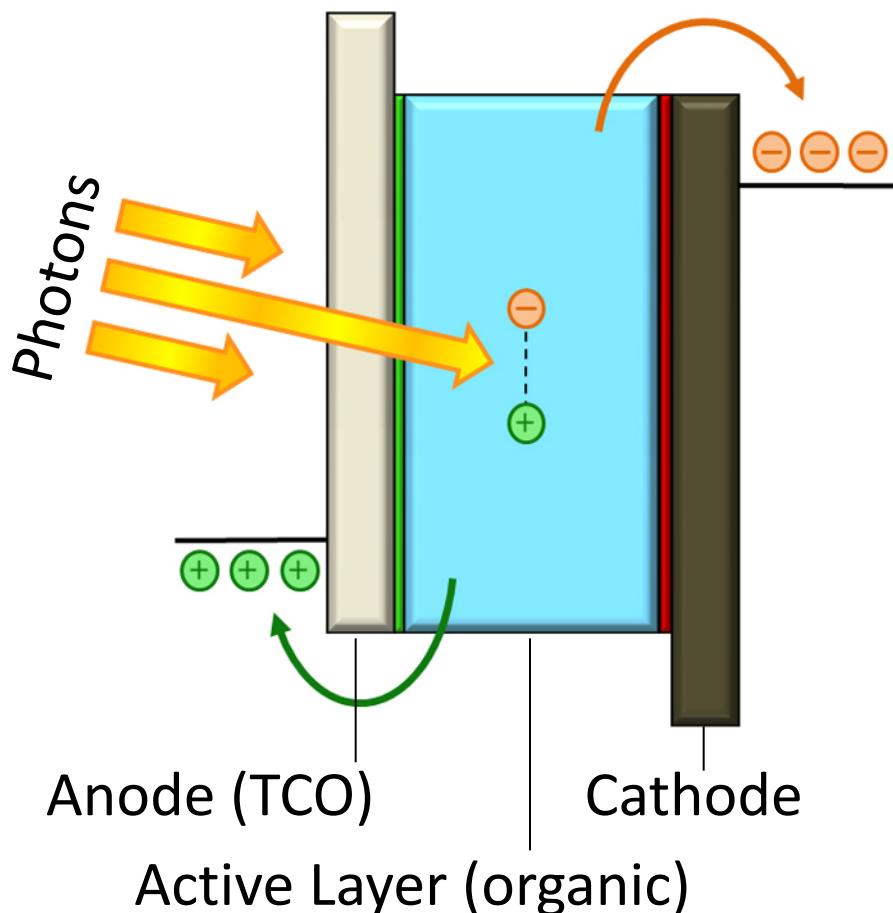
In collaboration with A. Sigdel, N.E. Widjonarko and J.J. Berry – CIS:SEM EFRC

Performance comparable to PEDOT:PSS on the first try!

Back to n-Type TCOs: The Importance of Work Functions

The Need for Ohmic Contacts

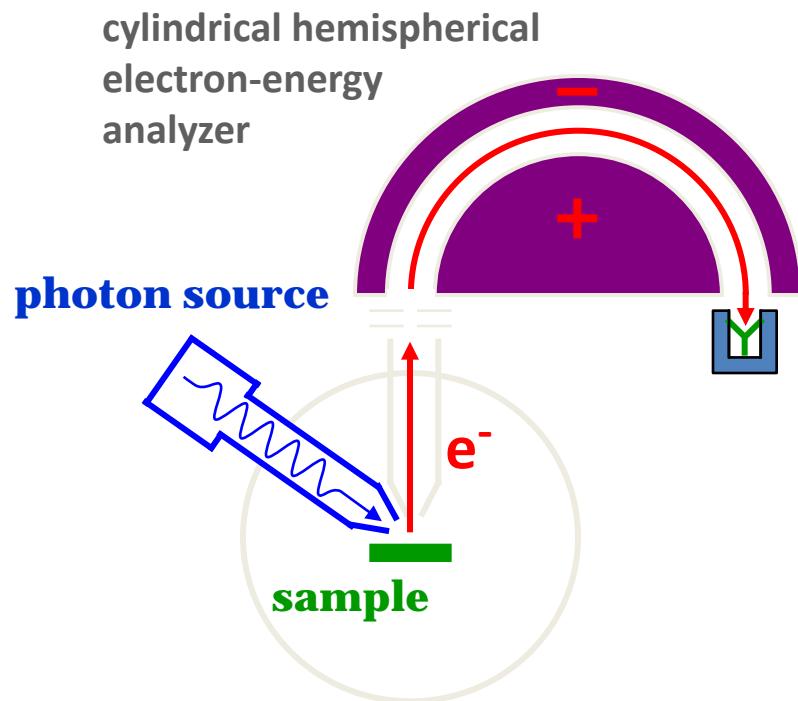
Organic Photovoltaic (OPV)



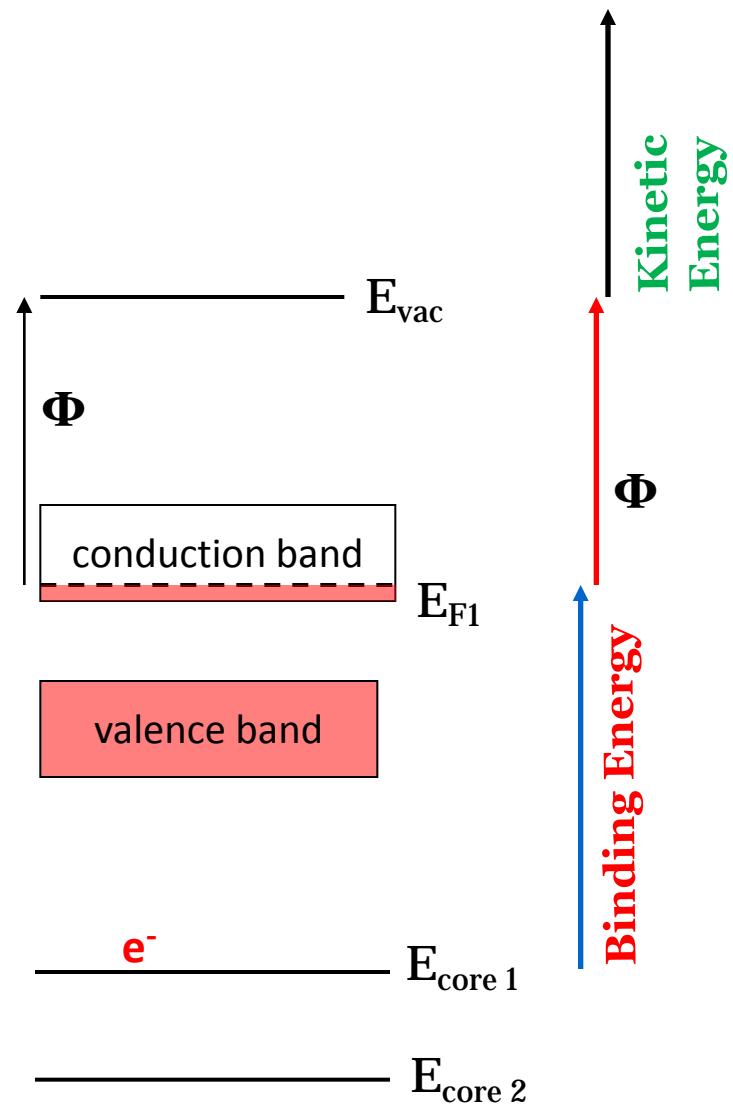
- TCOs play an integral role as electrically transparent contacts in solar cells
- Device performance depends on **Ohmic contacts** with electrodes
- Contact type depends on **band alignment** between layers

What is the Work Function? How is it Measured?

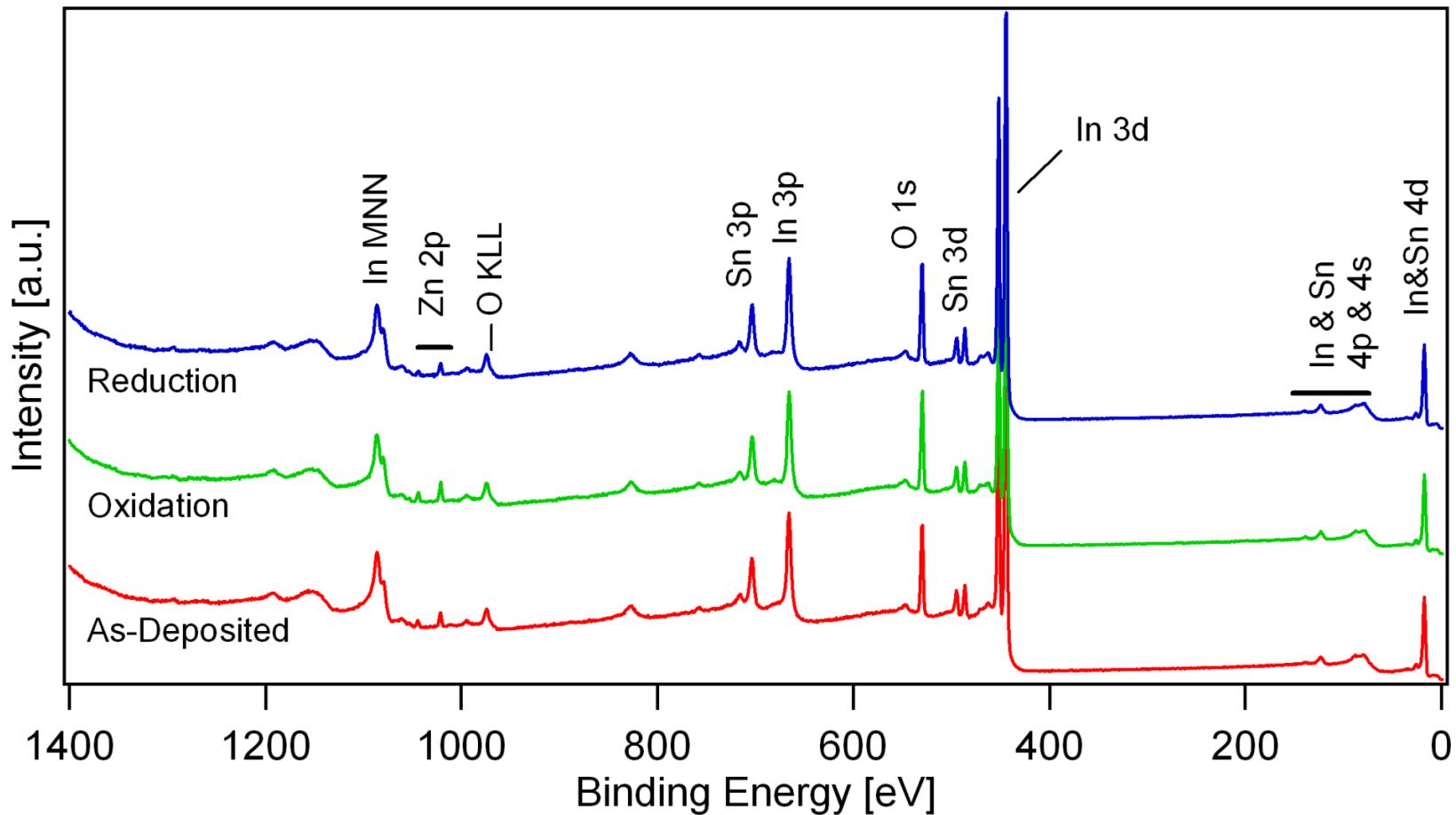
Photoelectron Spectroscopy



$$E_{BE} = h\nu_{\text{source}} - E_{\text{kinetic}} - \Phi_{\text{analyzer}}$$

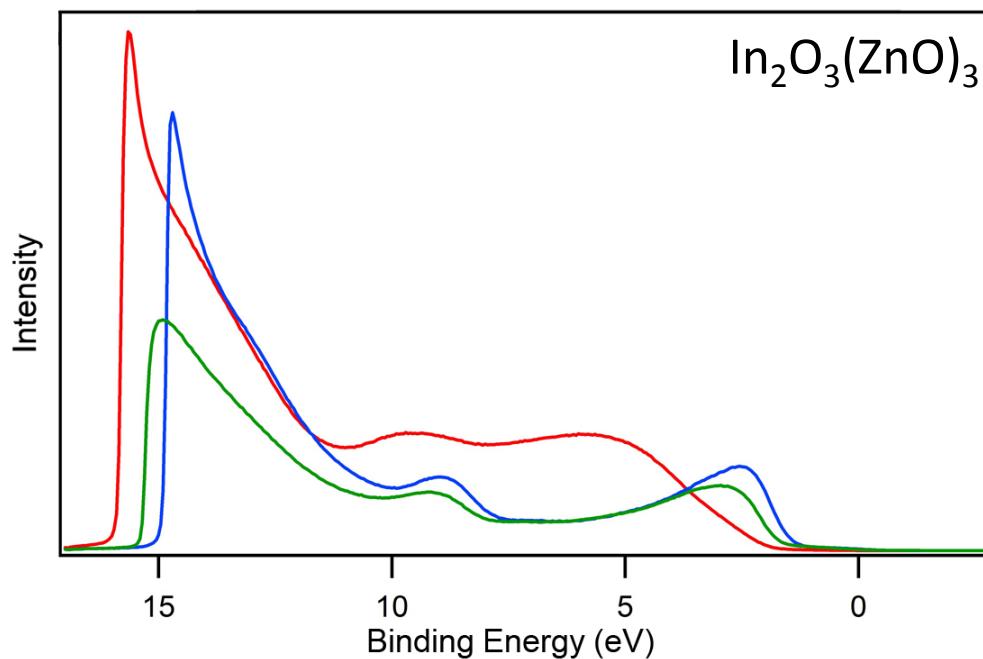
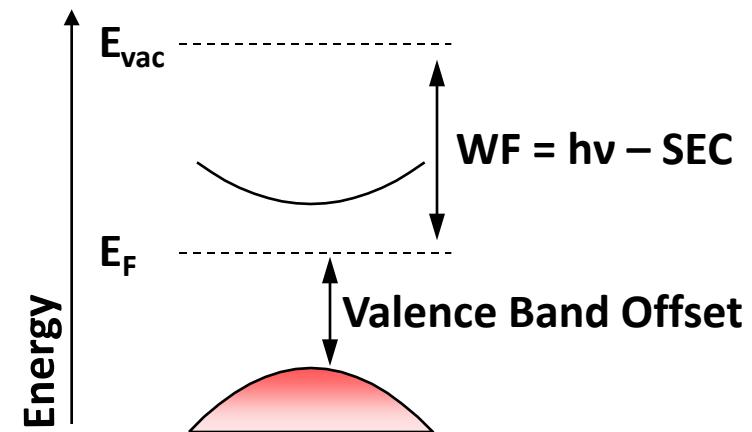
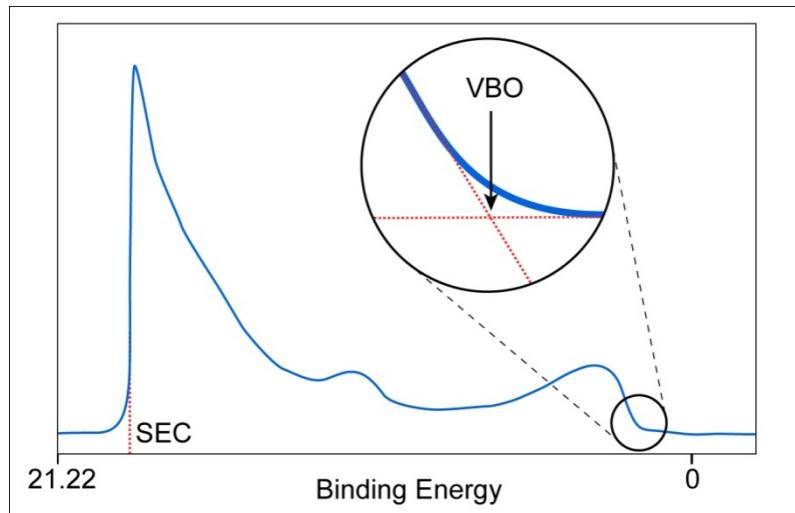


XPS Survey Spectra

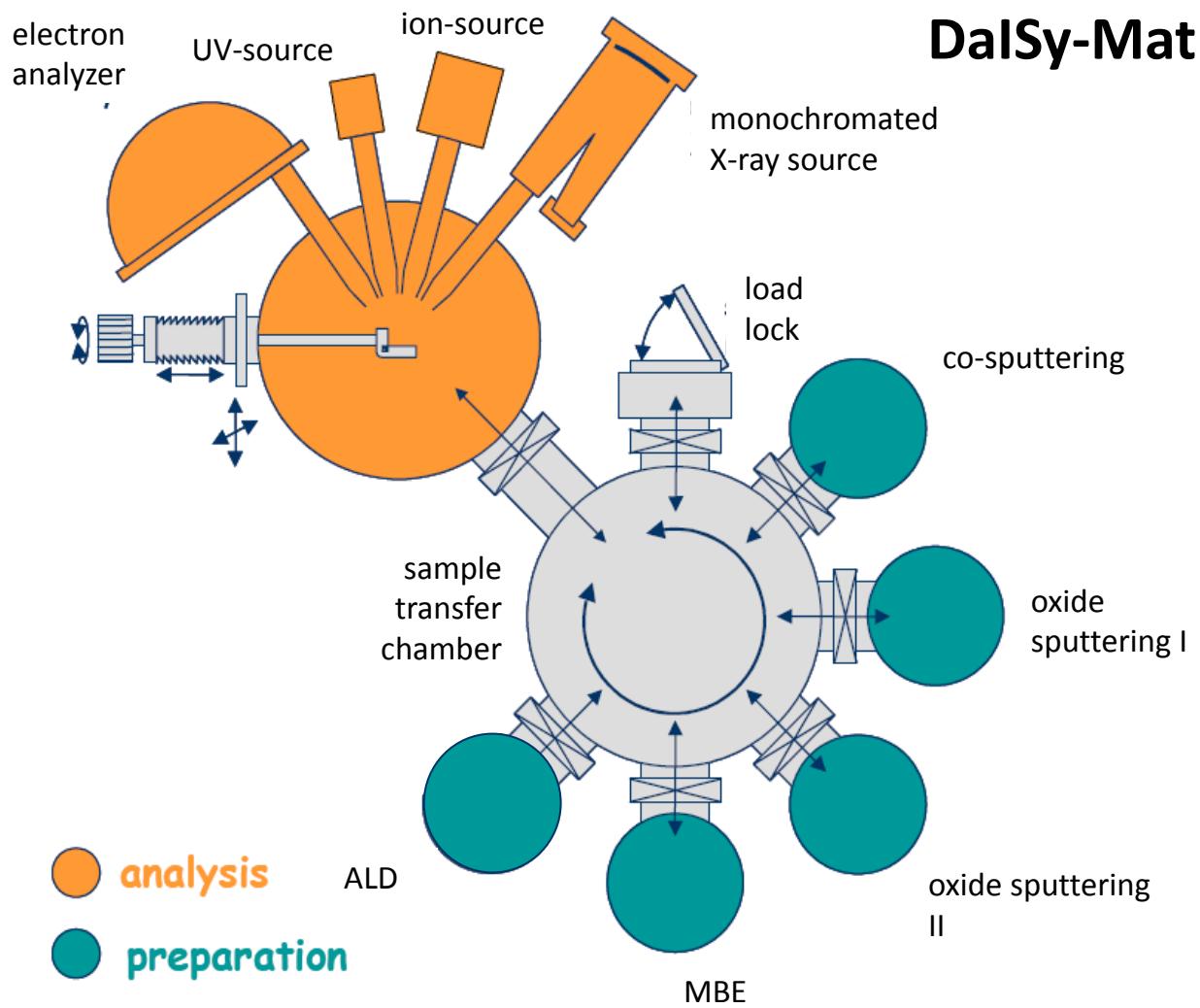


c-ZITO-10

UV Photoelectron Spectroscopy



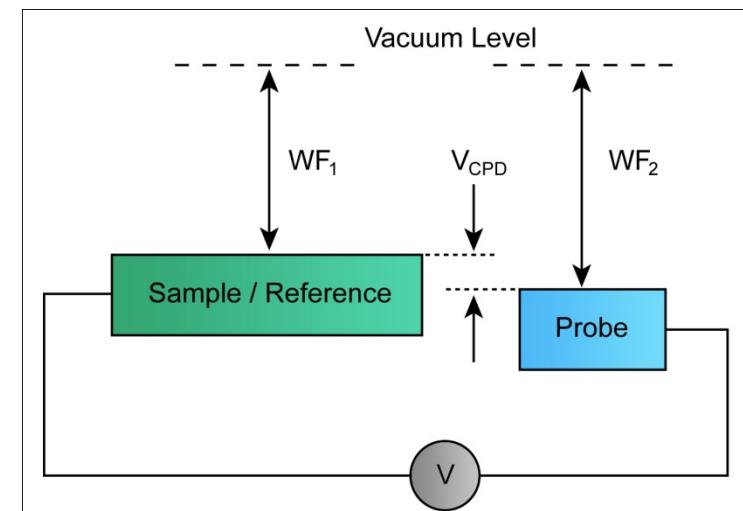
In Situ Photoelectron Spectroscopy



Kelvin Probe WF Measurements



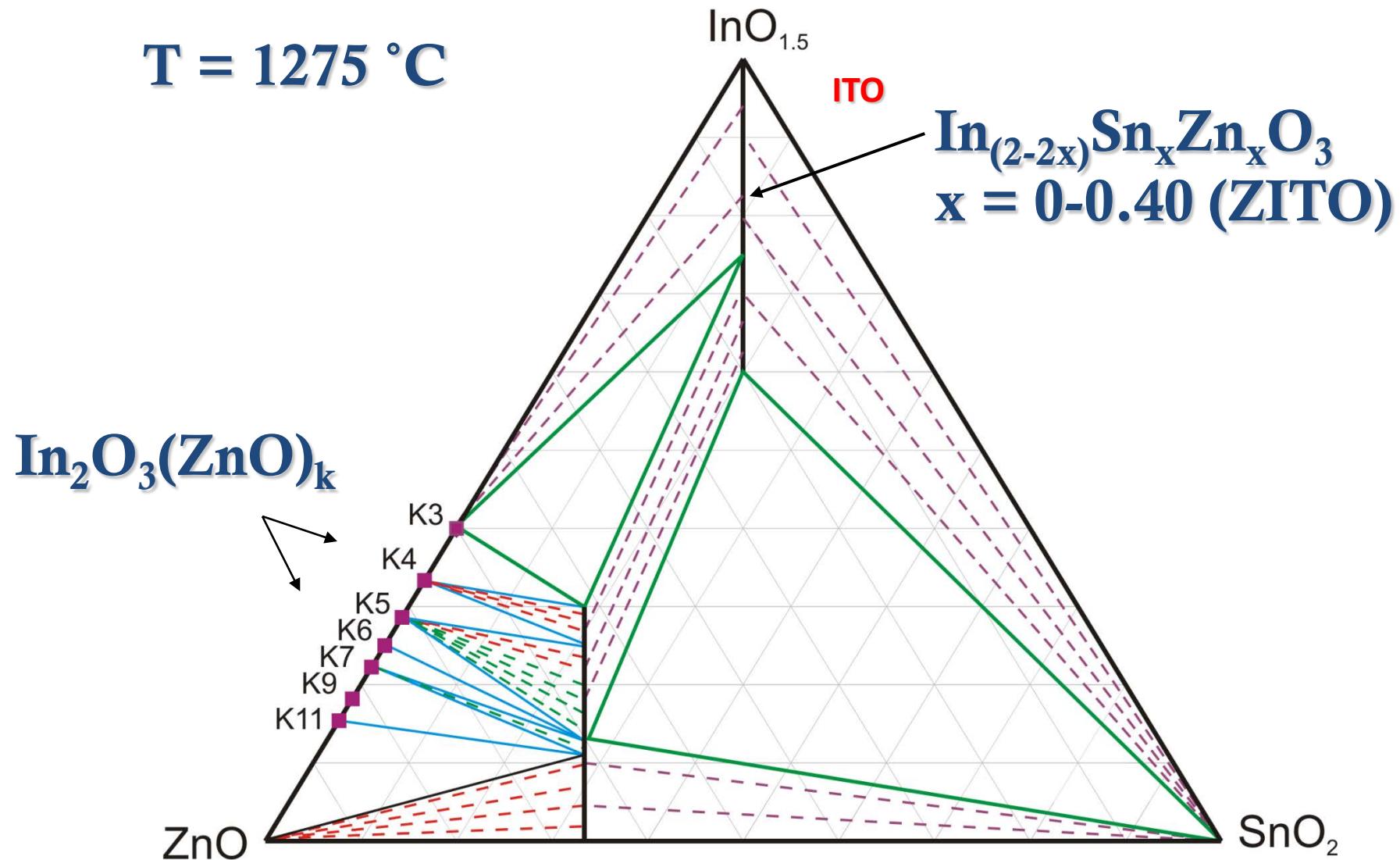
Kelvin Probe Method



Under ambient conditions!

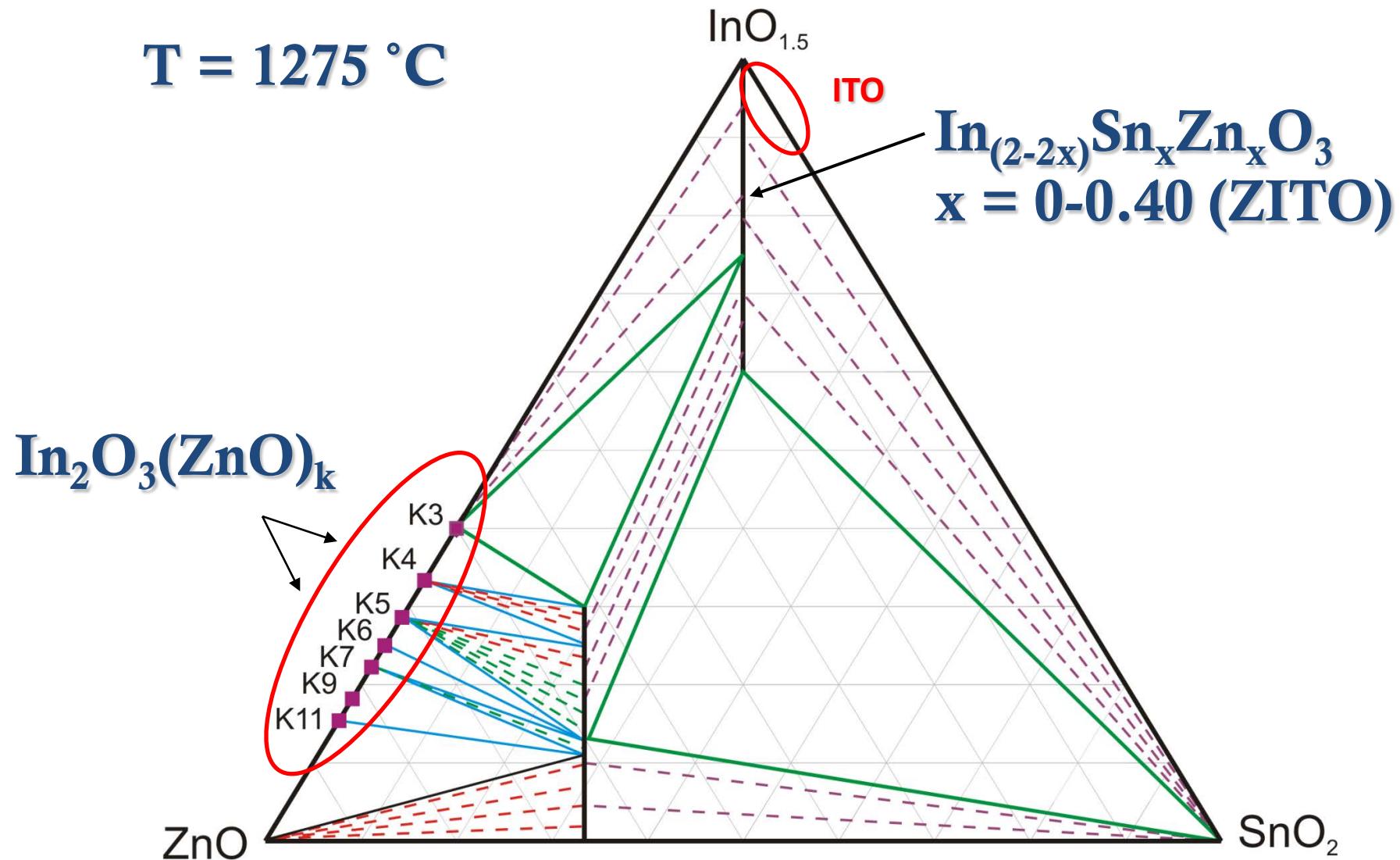
Zn-In-Sn-O System

T = 1275 °C

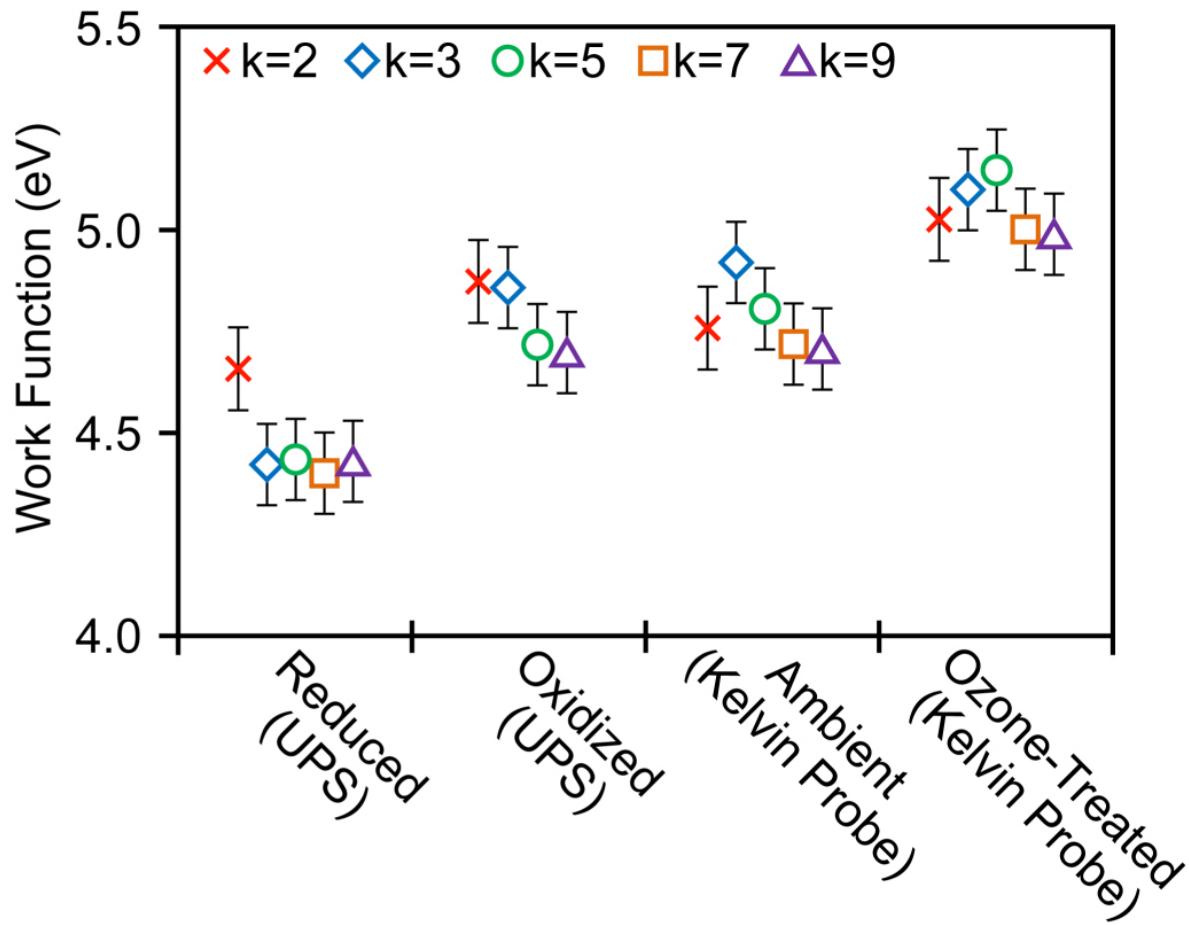


Zn-In-Sn-O System

T = 1275 °C

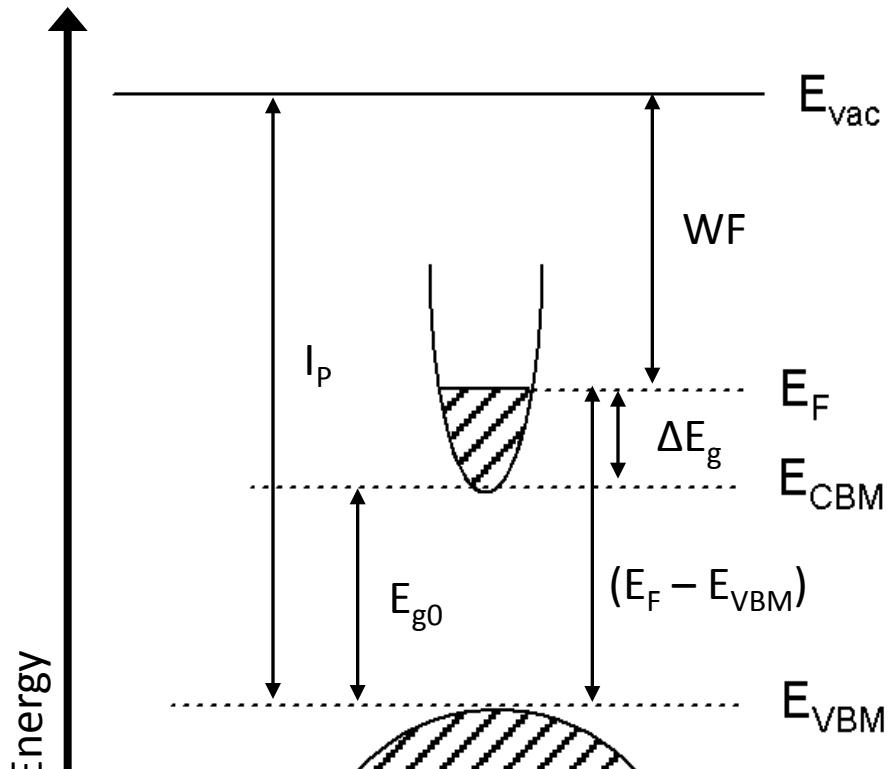


Comparison of KP and UPS



Some Surface Science Definitions

Some Basic Definitions



E_{vac} = vacuum level

E_F = Fermi level

E_{CBM} = conduction band minimum

E_{VBM} = valence band maximum

E_{g0} = fundamental band gap

ΔE_g = Burstein-Moss shift

I_p = ionization potential

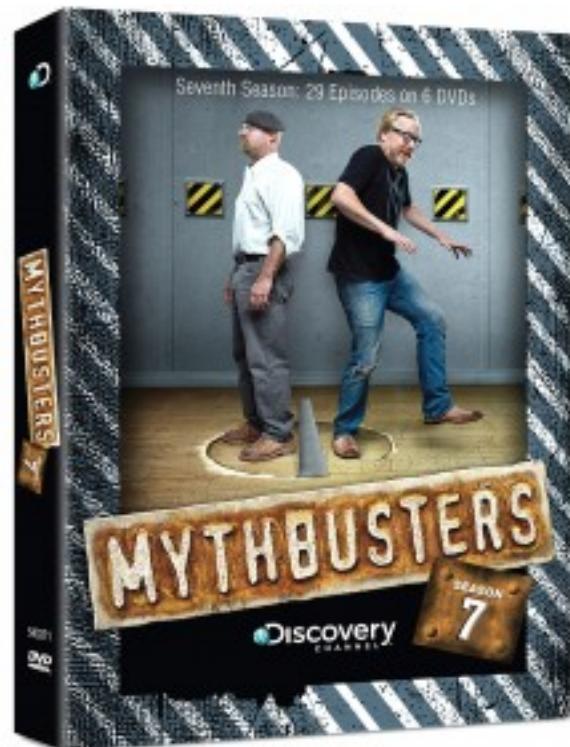
$(E_F - E_{VBM})$ = Fermi level position

WF = work function (Φ)

Debunking Work Function Myths

TCO Work Function Myths

- Every material has a unique work function
- The work function of a given oxide's surface is a constant
- The only way to change the work function of an oxide surface is “extrinsically” (e.g., by surface adsorbates)*

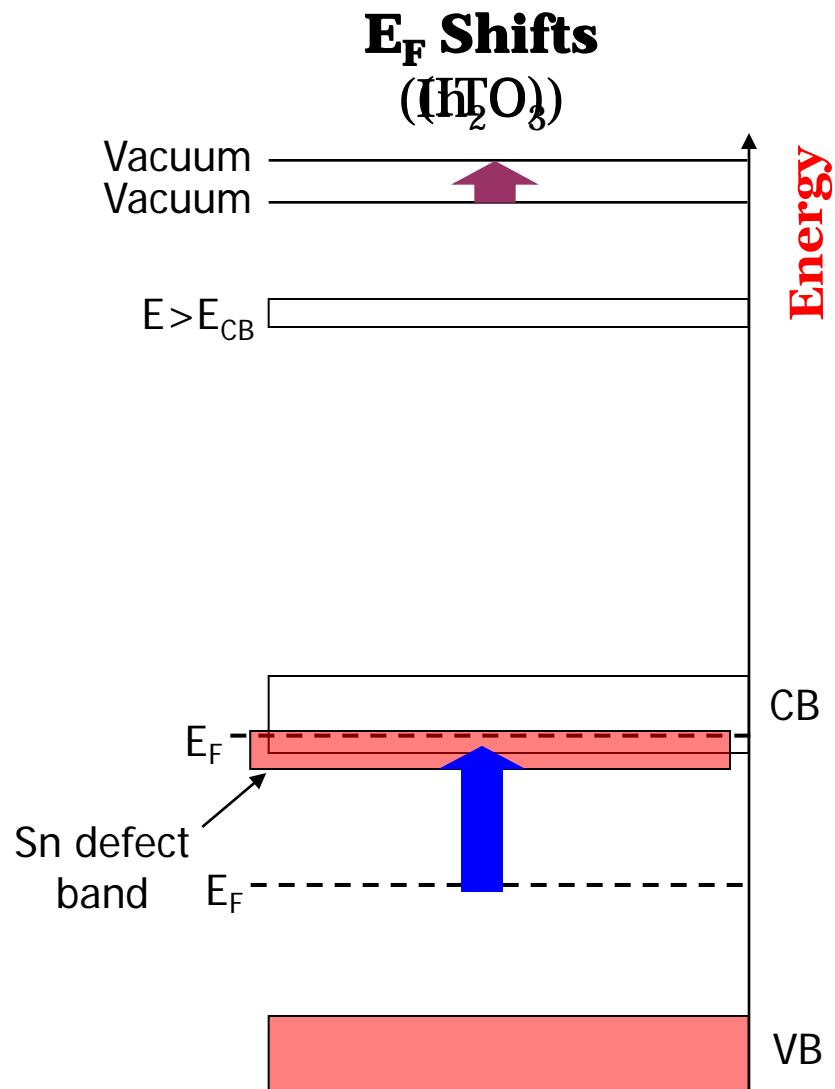


* For example, Neal Armstrong et al., *Accts. Chem. Res.*, 42 (11) 1748 (2009).

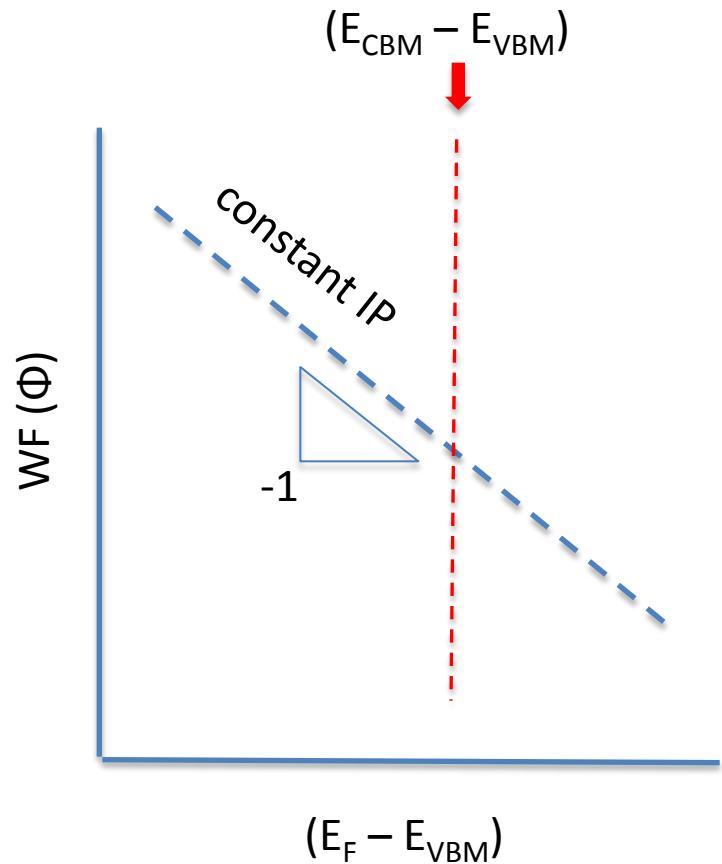
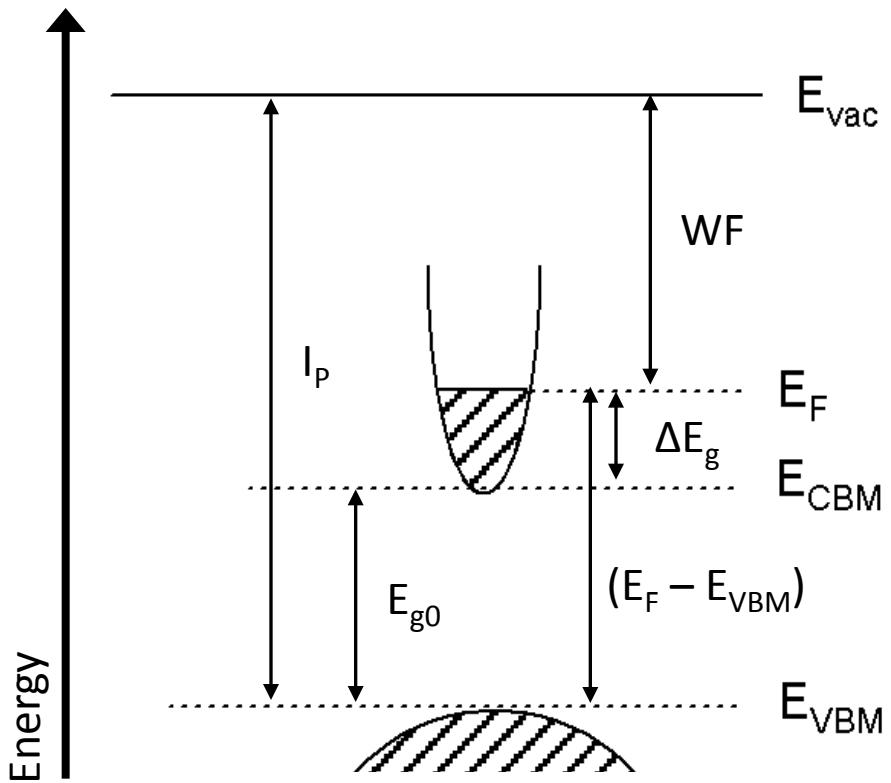
Manipulating Work Functions

How to Modify Work Function?

- Two ways:
 - Shift the Fermi level position ($E_F - E_{VBM}$) can change independently with doping
 - Change the Ionization potential ($E_{vac} - E_{VBM}$) can change independently with surface dipole changes (assuming E_g is constant)

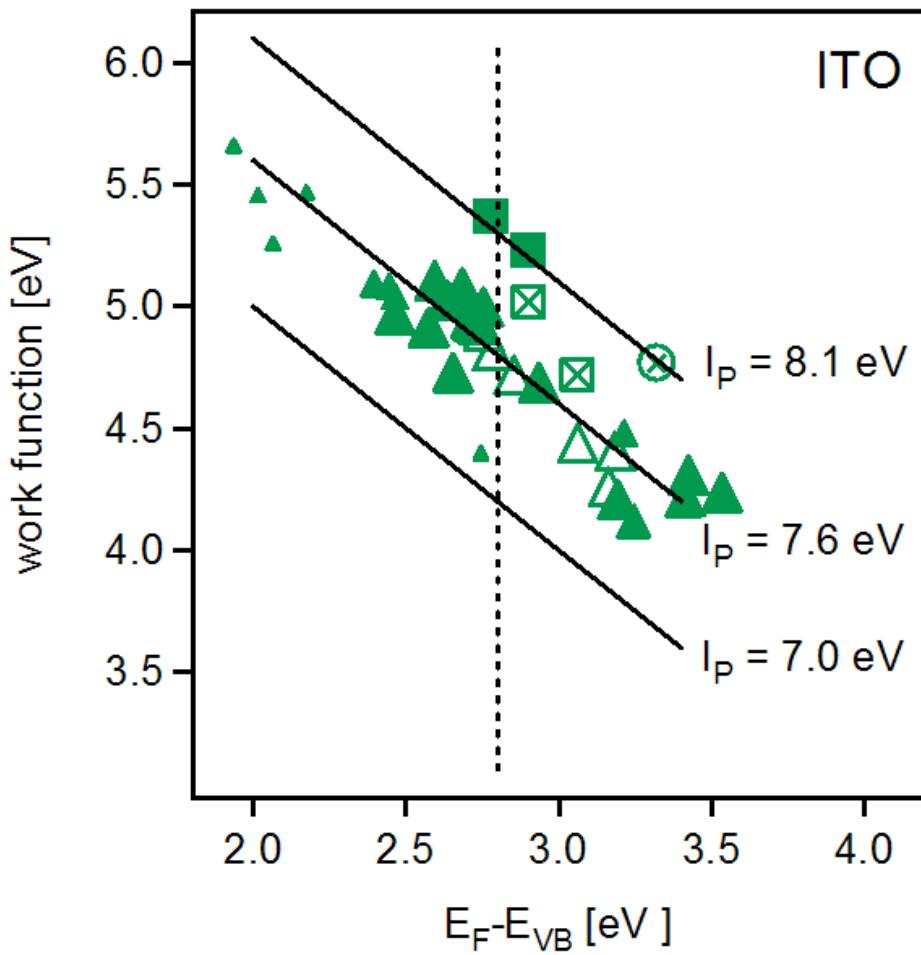


Ionization Potential Plots



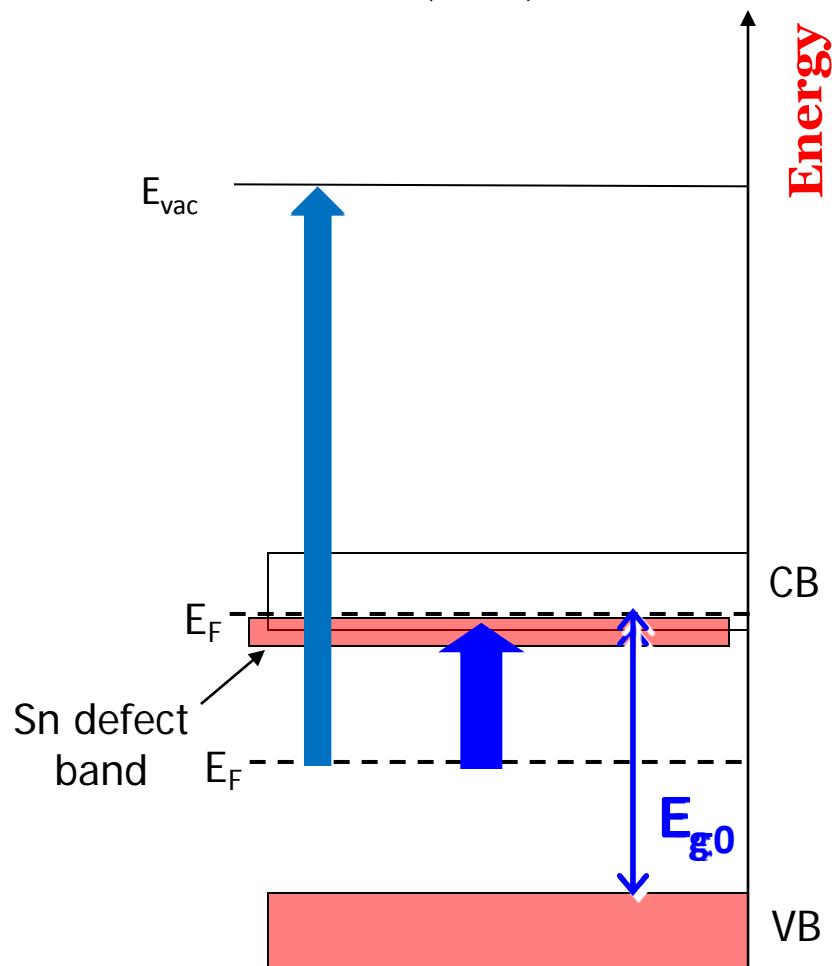
$$I_p = (E_F - E_{VBM}) + WF(\Phi) \rightarrow WF(\Phi) = I_p - (E_F - E_{VBM})$$

Changing Fermi Level Position

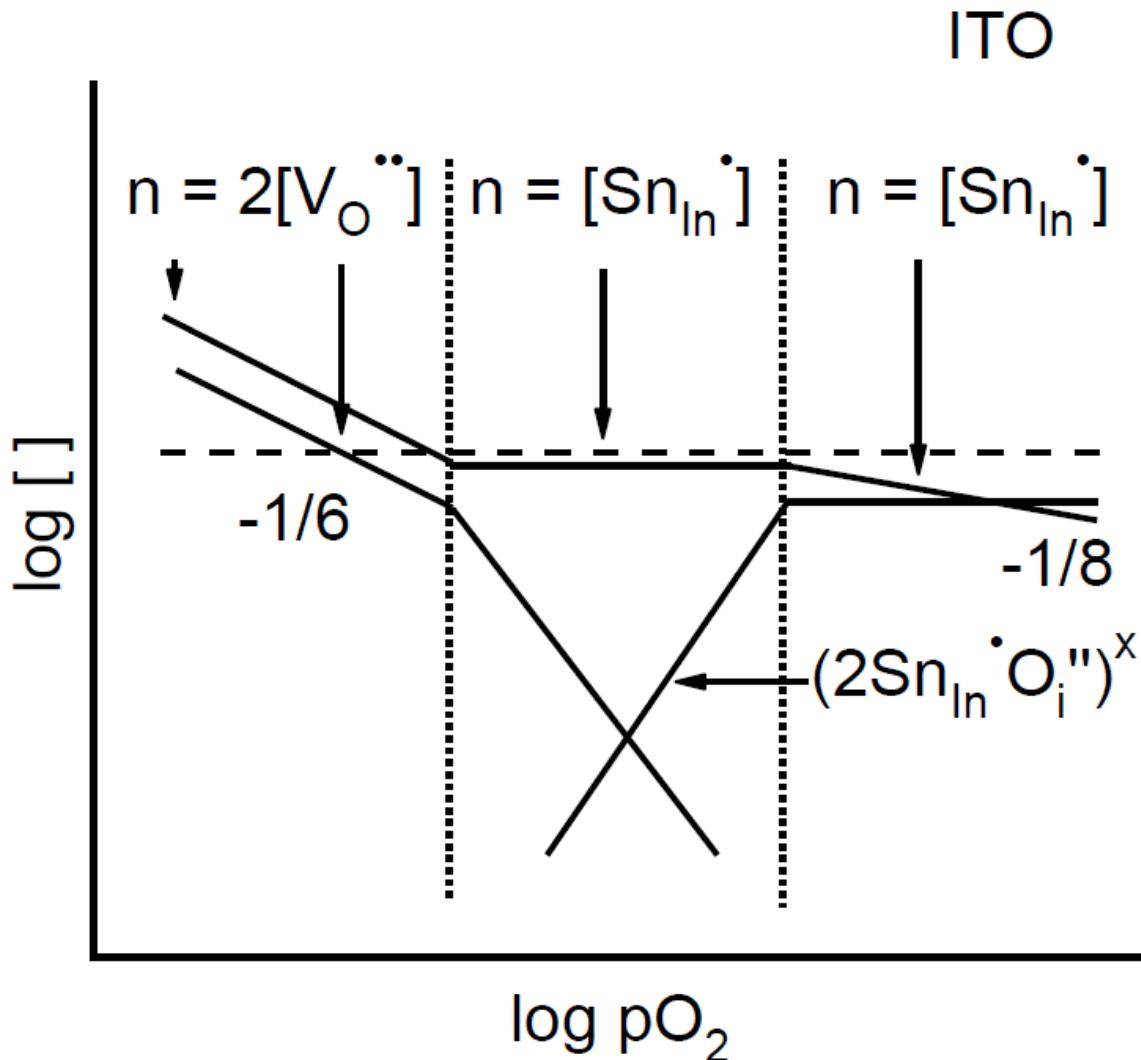


$$IP = (E_F - E_{VB}) + WF$$

**Burstein-Moss Shift
(ITO)**

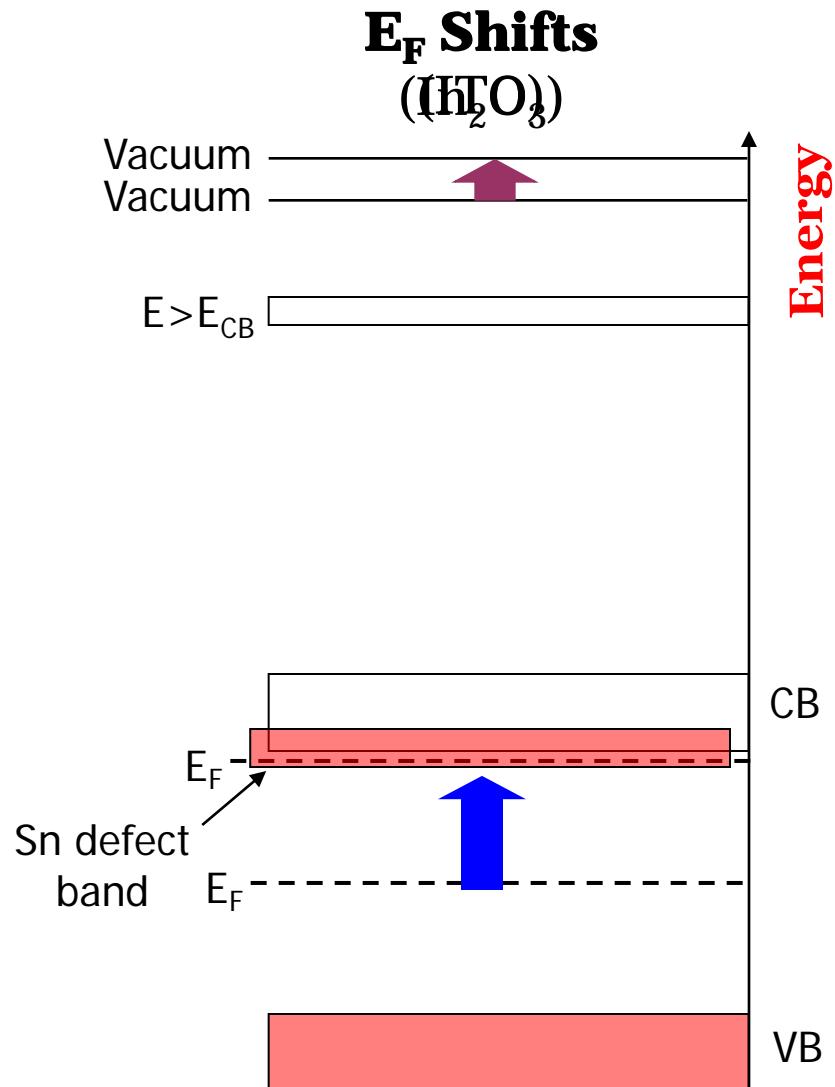


ITO Defect Chemistry



How to Modify Work Function?

- Two ways:
 - Shift the Fermi level position ($E_F - E_{VBM}$) can change independently with doping
 - Change the Ionization potential ($E_{vac} - E_{VBM}$) can change independently with surface dipole changes (assuming E_g is constant)



Surface Orientation Effects

Silver

Surface	Work Function	Polycrystalline Work Function
Ag (111)	4.74 eV	
Ag (100)	4.64 eV	
Ag (110)	4.52 eV	
Au(poly)		4.26 eV

Gold

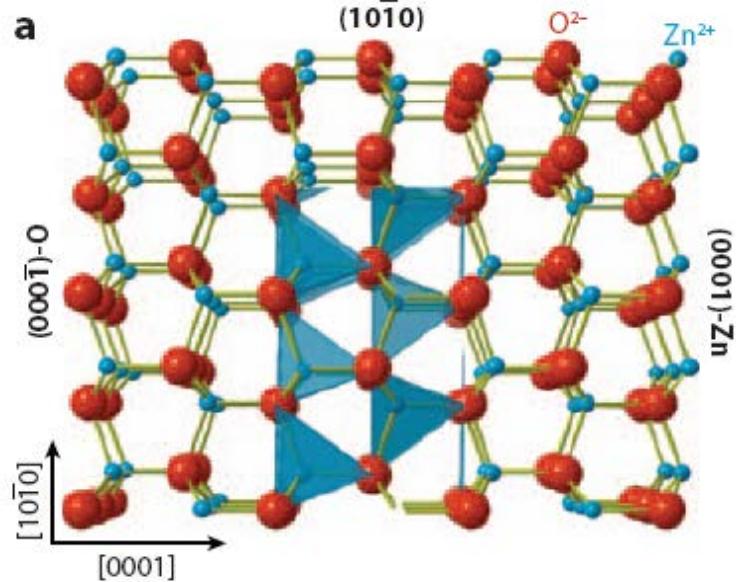
Surface	Work Function	Polycrystalline Work Function
Au (111)	5.31 eV	
Au (100)	5.47 eV	
Au (110)	5.37 eV	
Au(poly)		5.10 eV

Note: close-packed surfaces have high work functions; polycrystalline specimens represent averages with low-work function orientations.

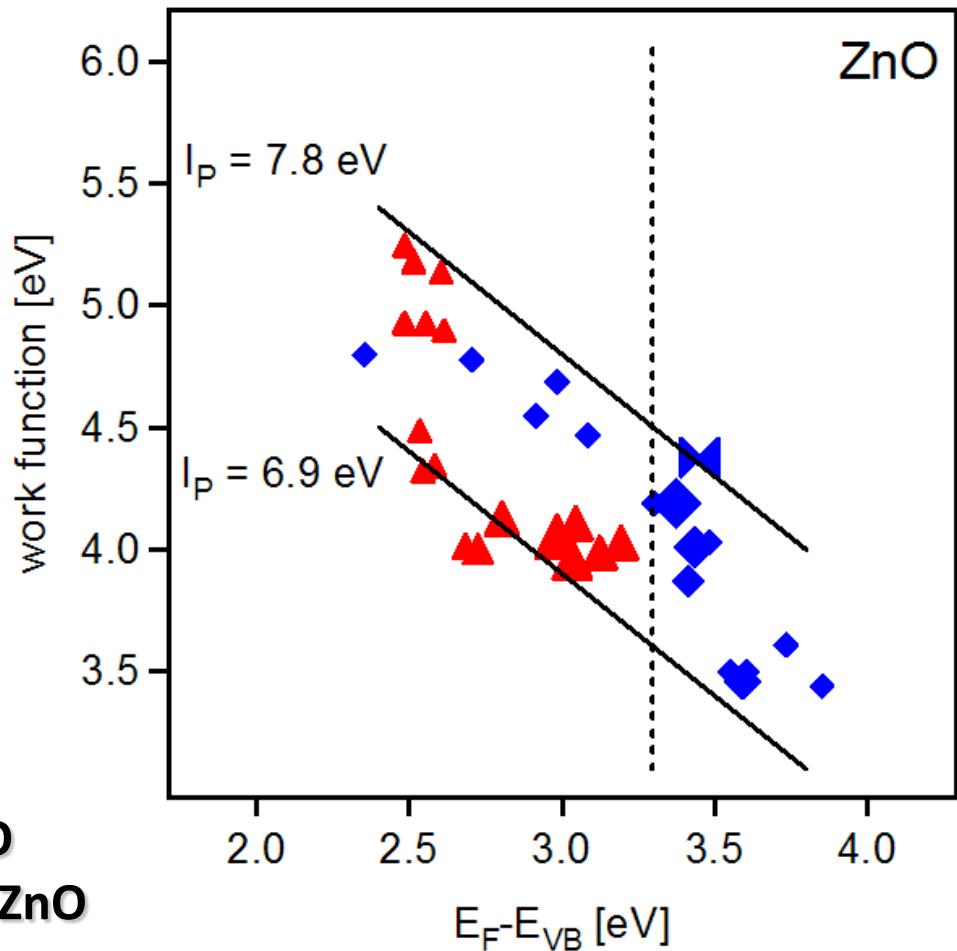
*H. B. Michaelson, The Work Function of the Elements and Its Periodicity,
J. Appl. Phys. 48 (1977) 4729.*

ZnO-Surface Orientations

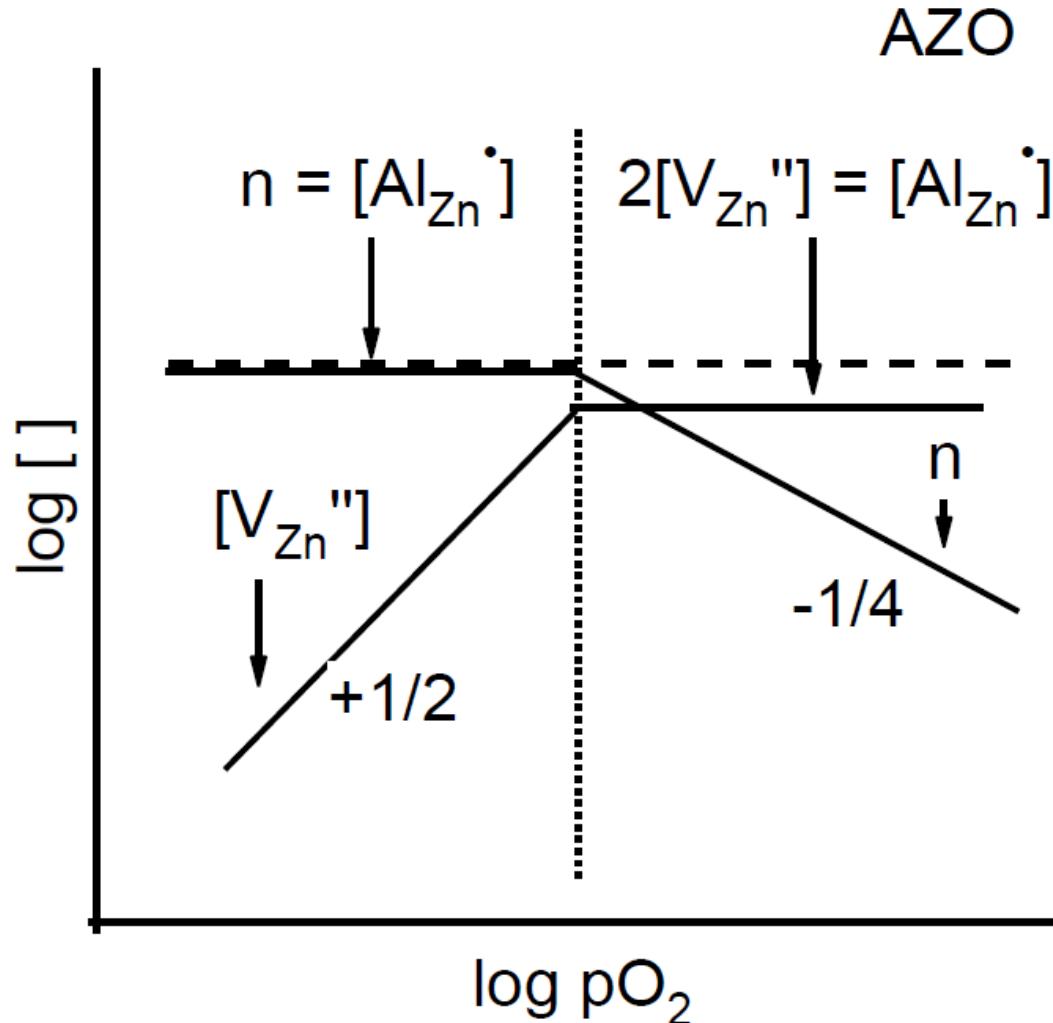
ZnO has polar and non-polar surface terminations



Red = ZnO
Blue = Al:ZnO

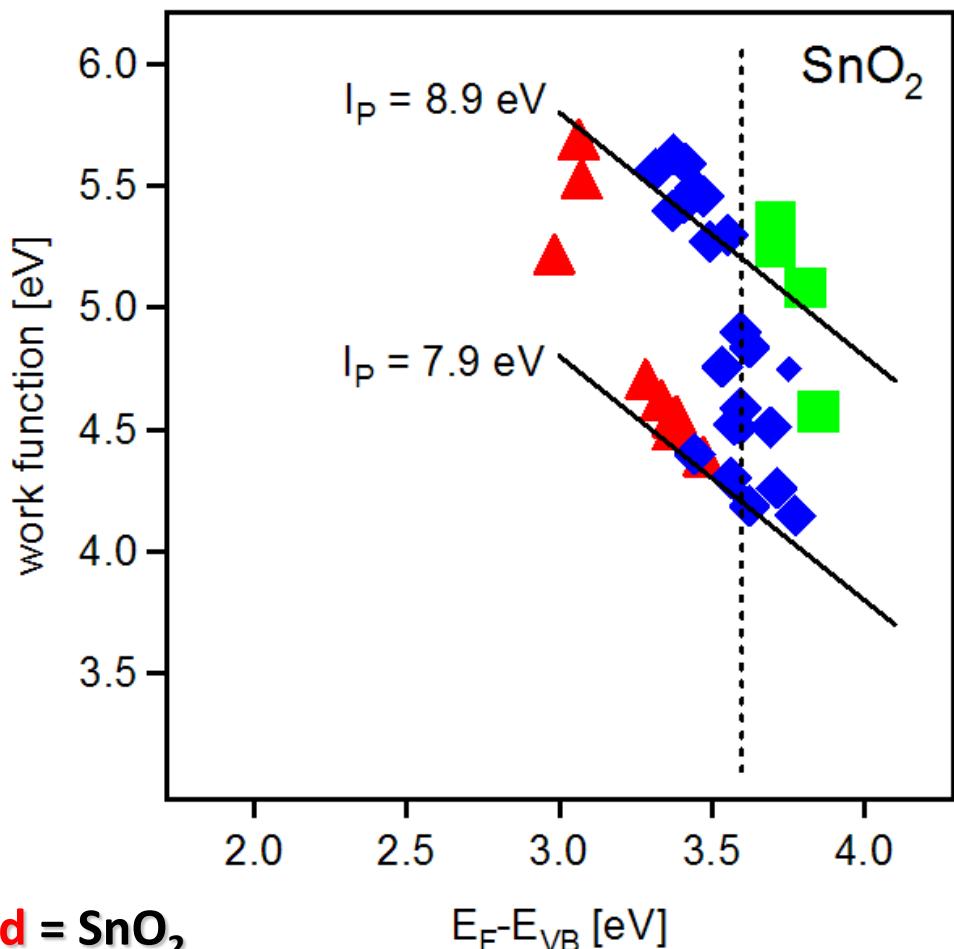
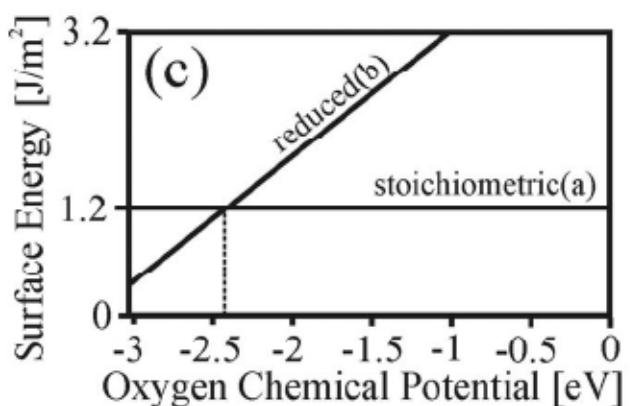
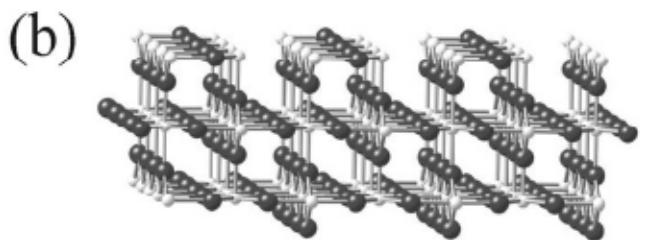
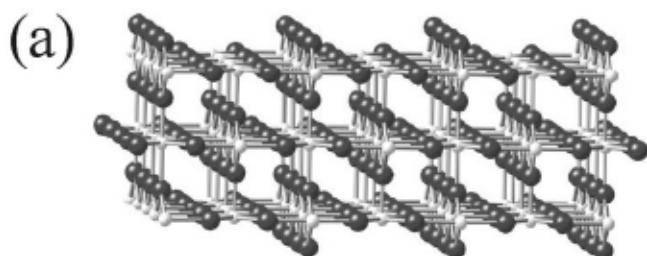


ZnO:Al Defect Chemistry



SnO_2 Surface Terminations

(110) Surface

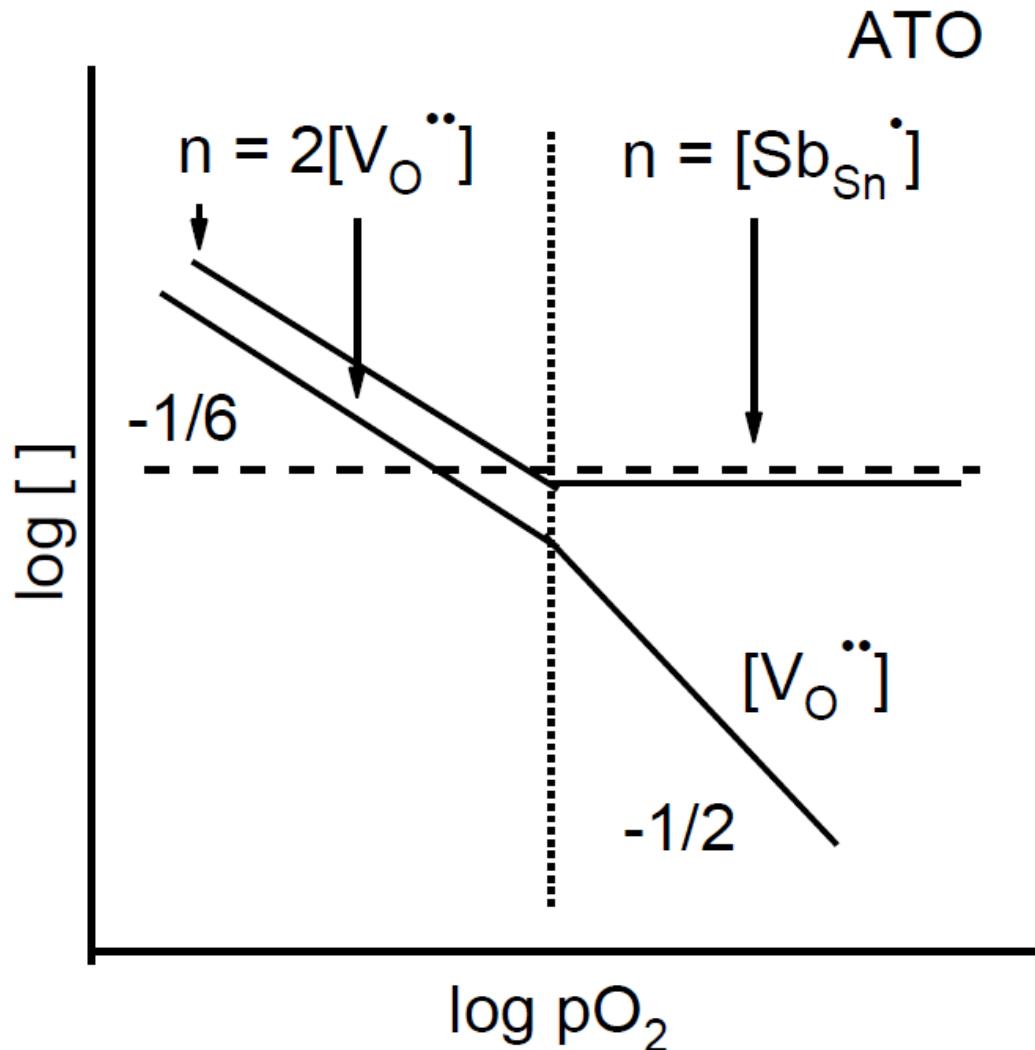


Red = SnO_2

Blue = $\text{Sb}:\text{SnO}_2$

Green = Bulk $\text{Sb}:\text{SnO}_2$

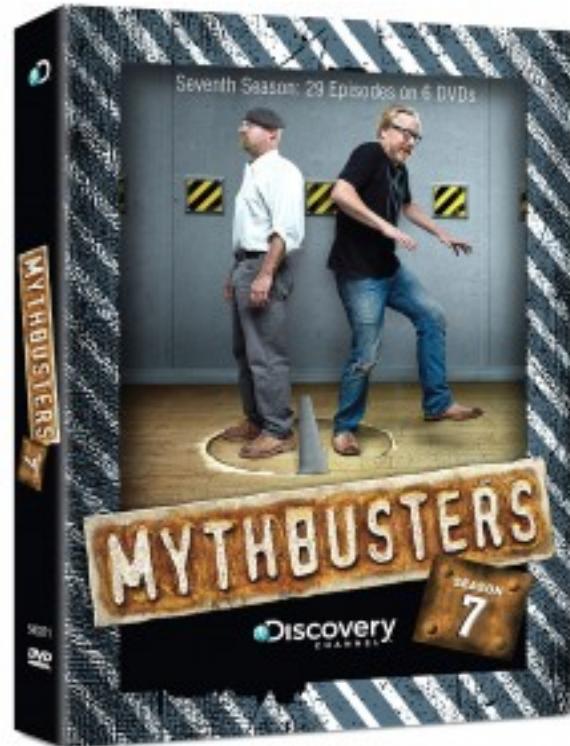
$\text{SnO}_2:\text{Sb}$ Defect Chemistry



TCO Work Function Truths

$$IP = (E_F - E_{VBM}) + WF$$

- The WF of an oxide surface decreases linearly as Fermi level increases (if IP remains constant)
- The IP (WF) of an oxide surface can be changed by dipole modifications—surface orientation, surface termination, surface stoichiometry—(if Fermi level remains constant)
- We can therefore change oxide surface work functions both “intrinsically” and “extrinsically”*

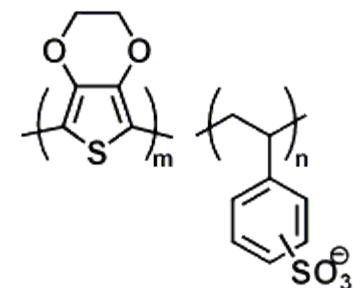


* For example, Neal Armstrong et al., *Accts. Chem. Res.*, 42 (11) 1748 (2009).

Motivation for New TCOs

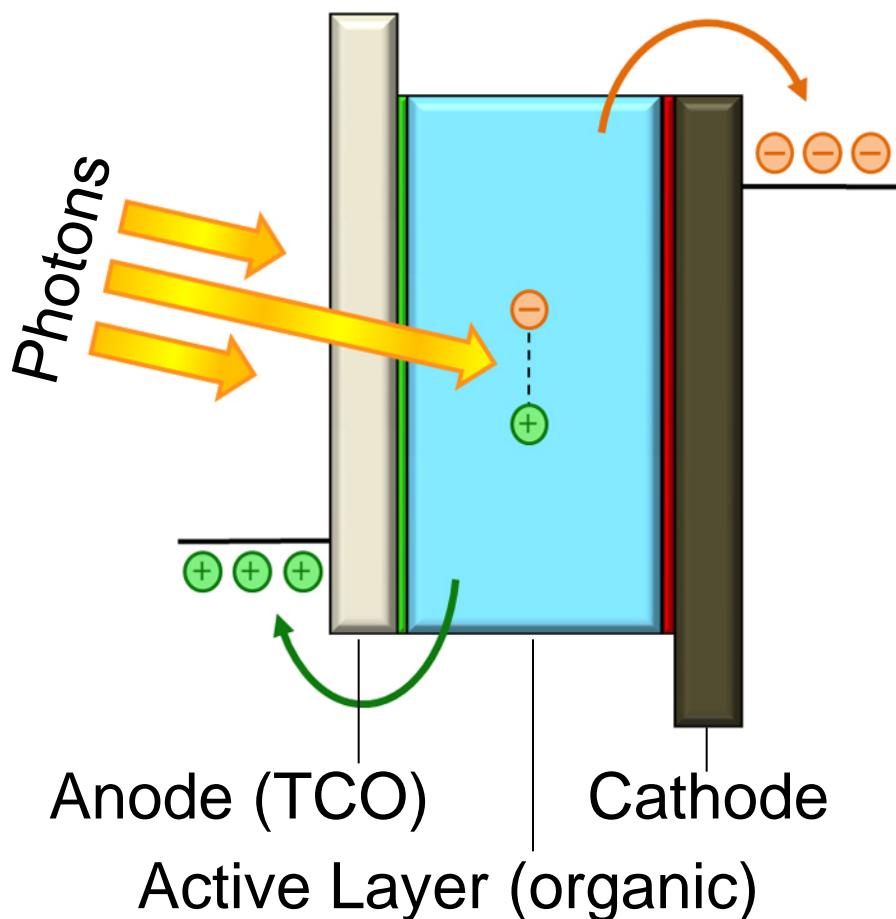
Why Do We Need New TCOs?

- Why do people use ITO?
 - Available
 - Good TCO (up to 10,000 S/cm conductivity, good transparency)
- Drawbacks to ITO
 - COST
 - In costs are volatile
 - STABILITY
 - ITO is etched by common barrier layer PEDOT:PSS
 - WORK FUNCTION
 - ITO work function is generally < 5eV



The Importance of TCOs in OPVs

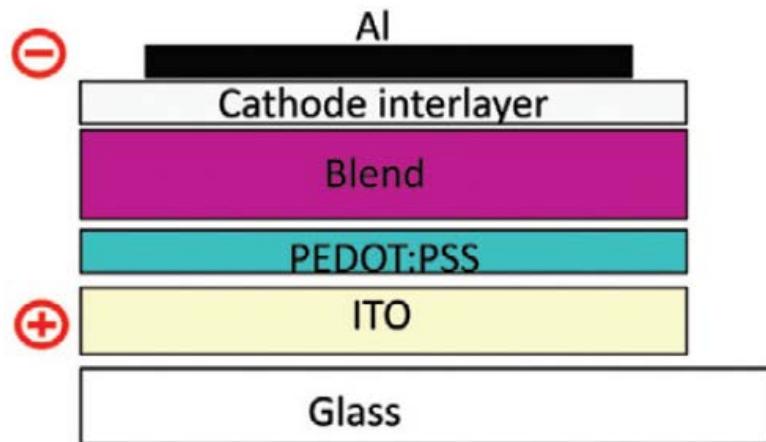
Organic Photovoltaic (OPV)



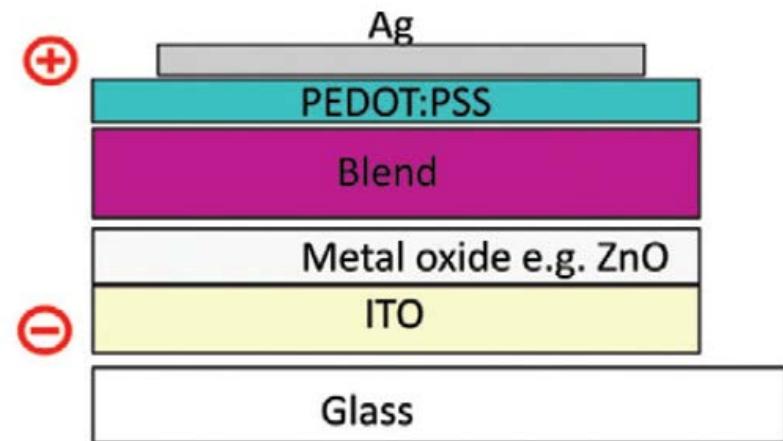
- TCOs play an integral role as electrically transparent contacts in solar cells
- Device performance depends on Ohmic contacts with electrodes
- Contact type depends on band alignment between layers

TCOs in Traditional/Inverted Cells

Traditional Polarity



Inverted Polarity



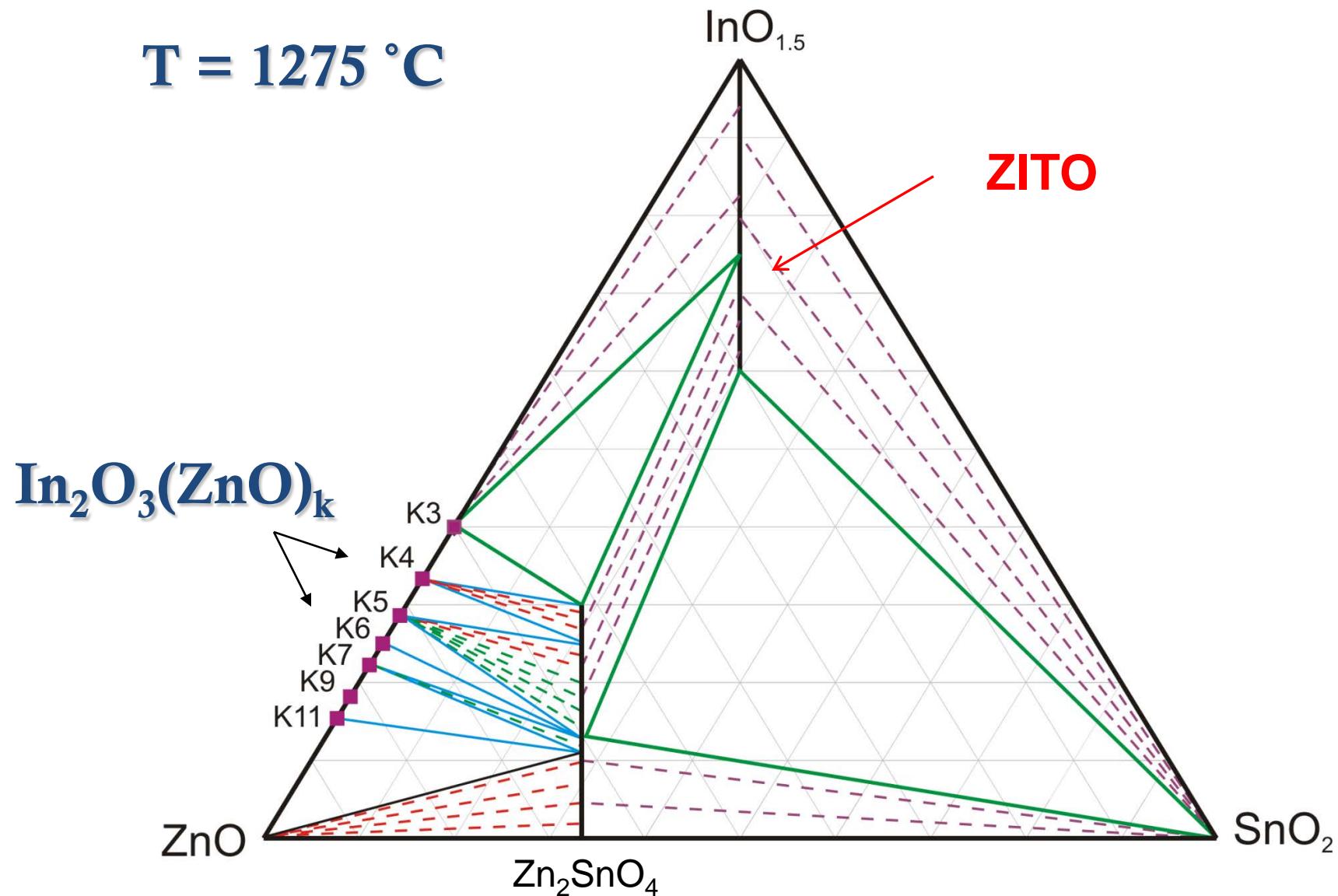
Want high work function: $> 5\text{eV}$

Want low work function: $< 4\text{eV}$

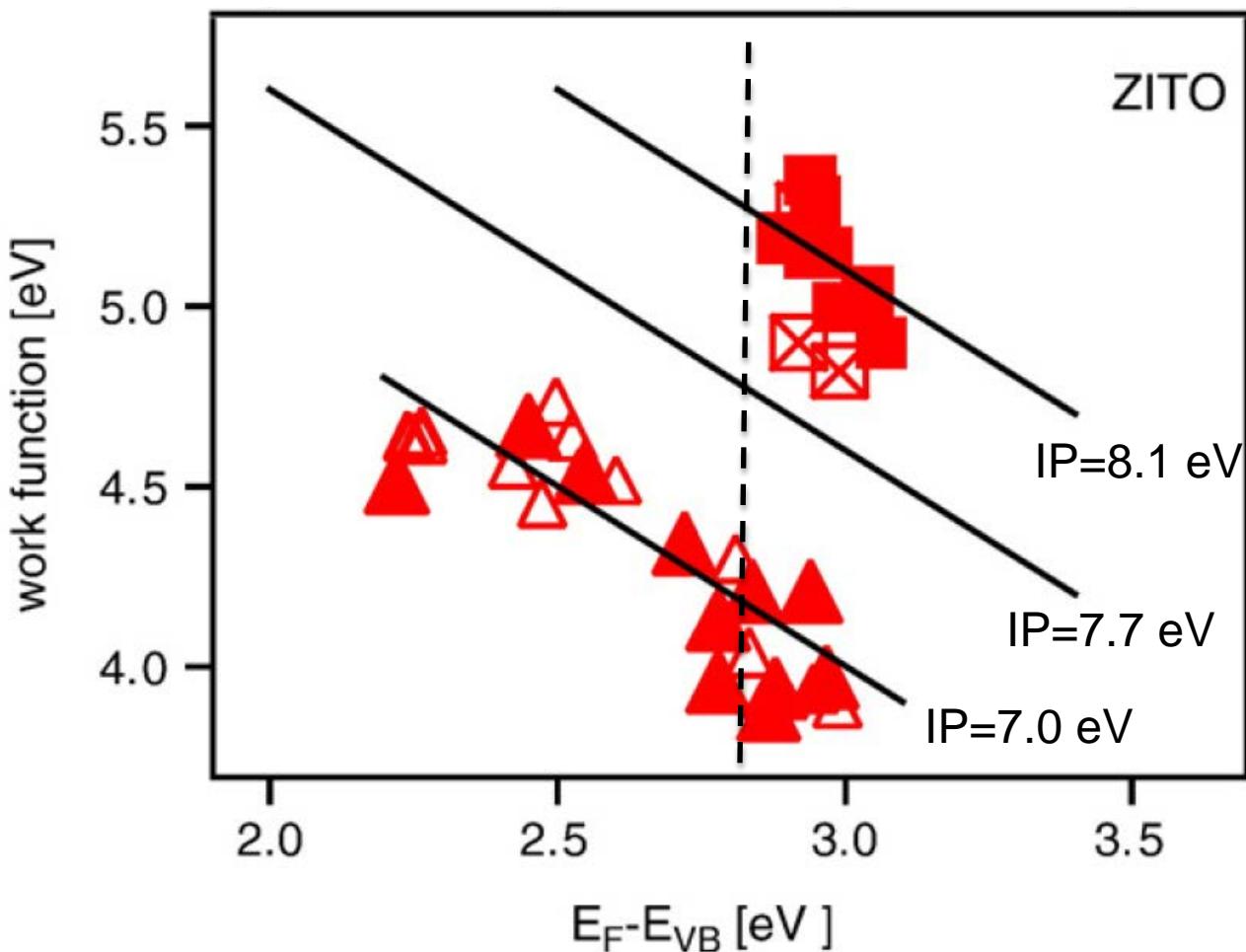
Both: Want high Fermi level (high conductivity)

The Zn-In-Sn-O System

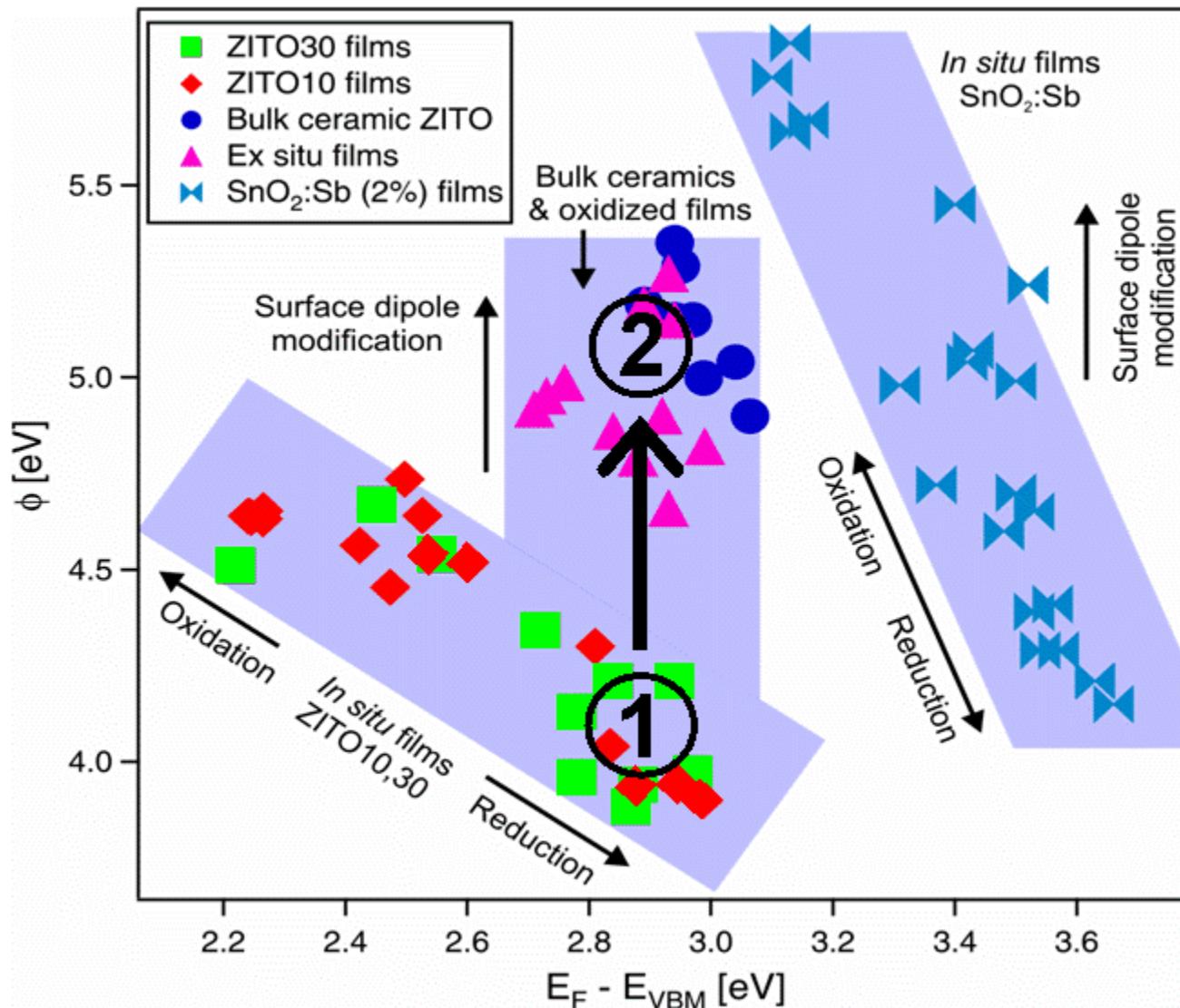
$T = 1275 \text{ } ^\circ\text{C}$



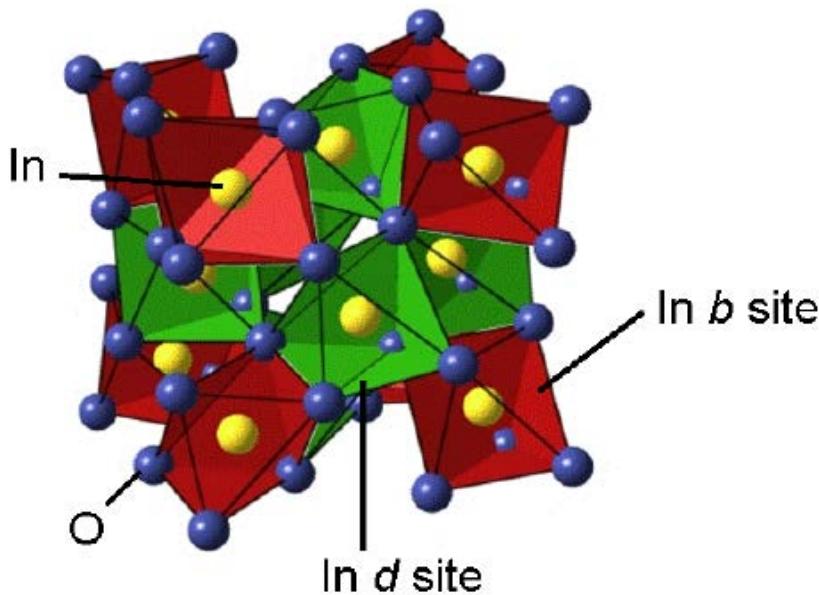
ZITO (Zn,Sn co-substituted ITO) Surfaces



Two-Step Processing



C-ZITO Bulk Structure: Bixbyite

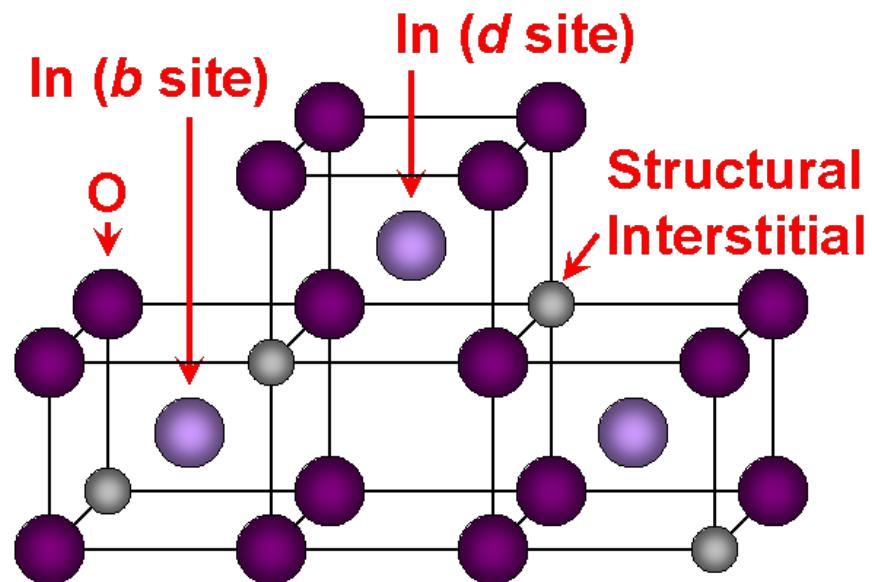


Blue = oxygen
Yellow = indium

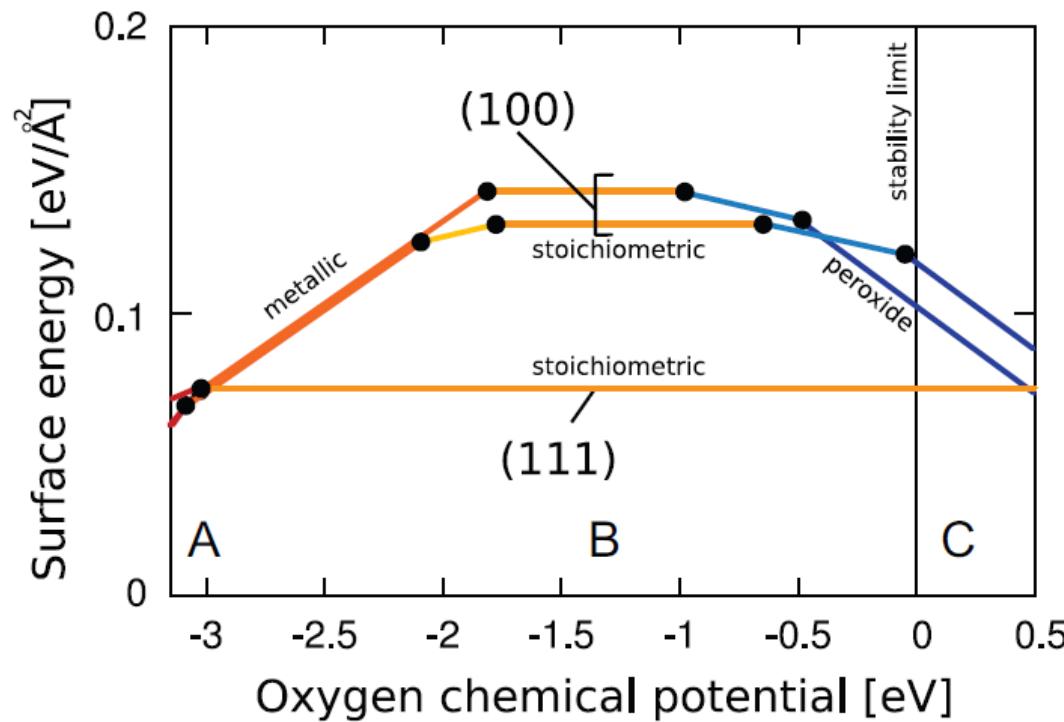
bixbyite = fluorite with
 $\frac{1}{4}$ of the anions missing

Two different cation positions

Structural oxygen interstitial positions

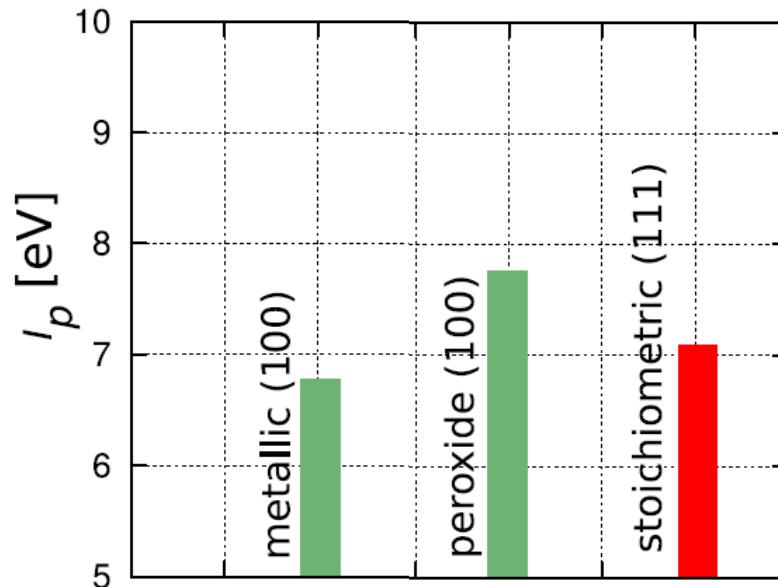


In_2O_3 Surfaces



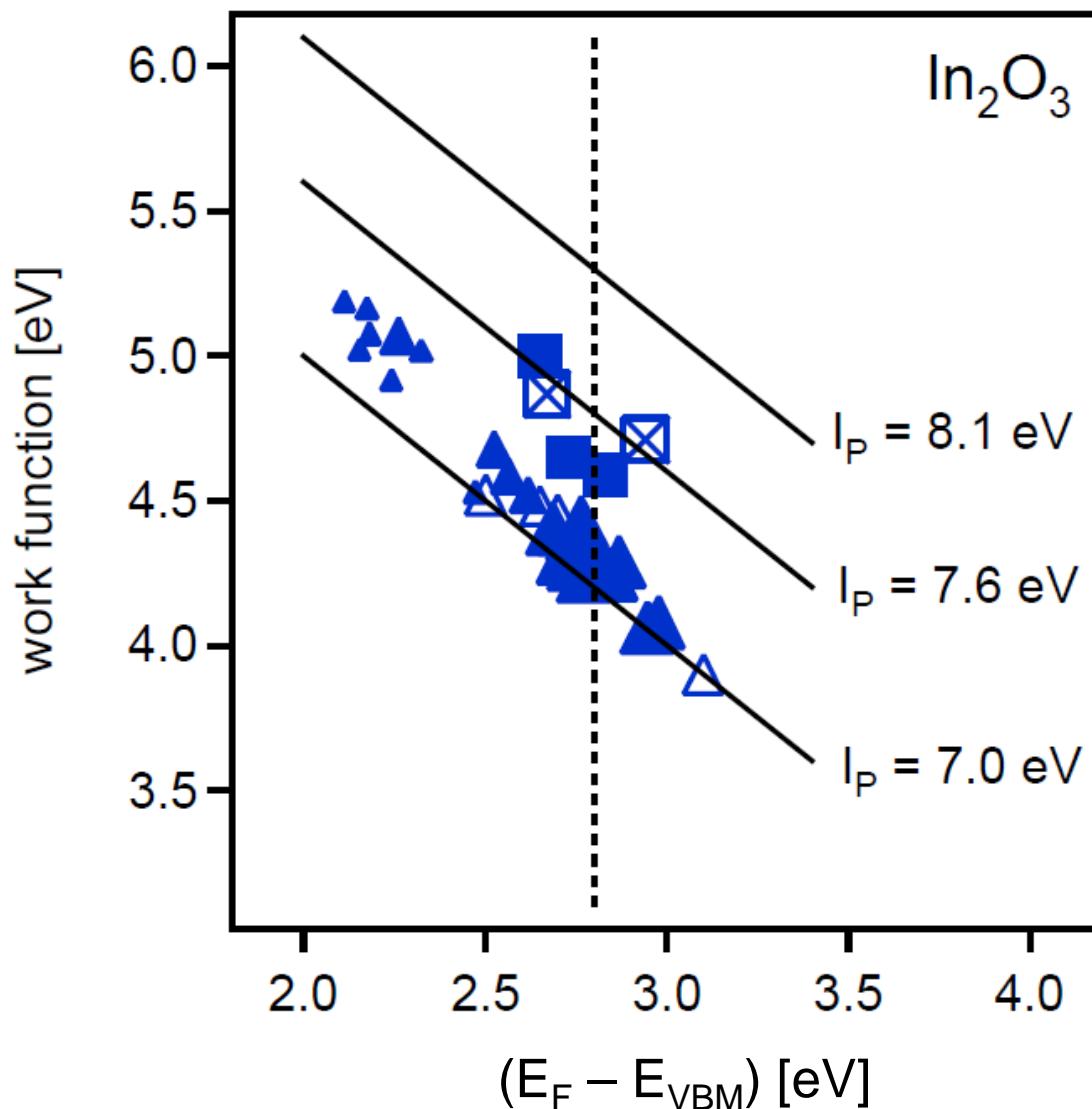
- High μ_O can produce a high In_2O_3 work function on a peroxidized (100) surface)
- Polycrystalline materials will exhibit inhomogeneous surface work functions: “hot spots,” “cold spots”

Predicted Ionization Potentials

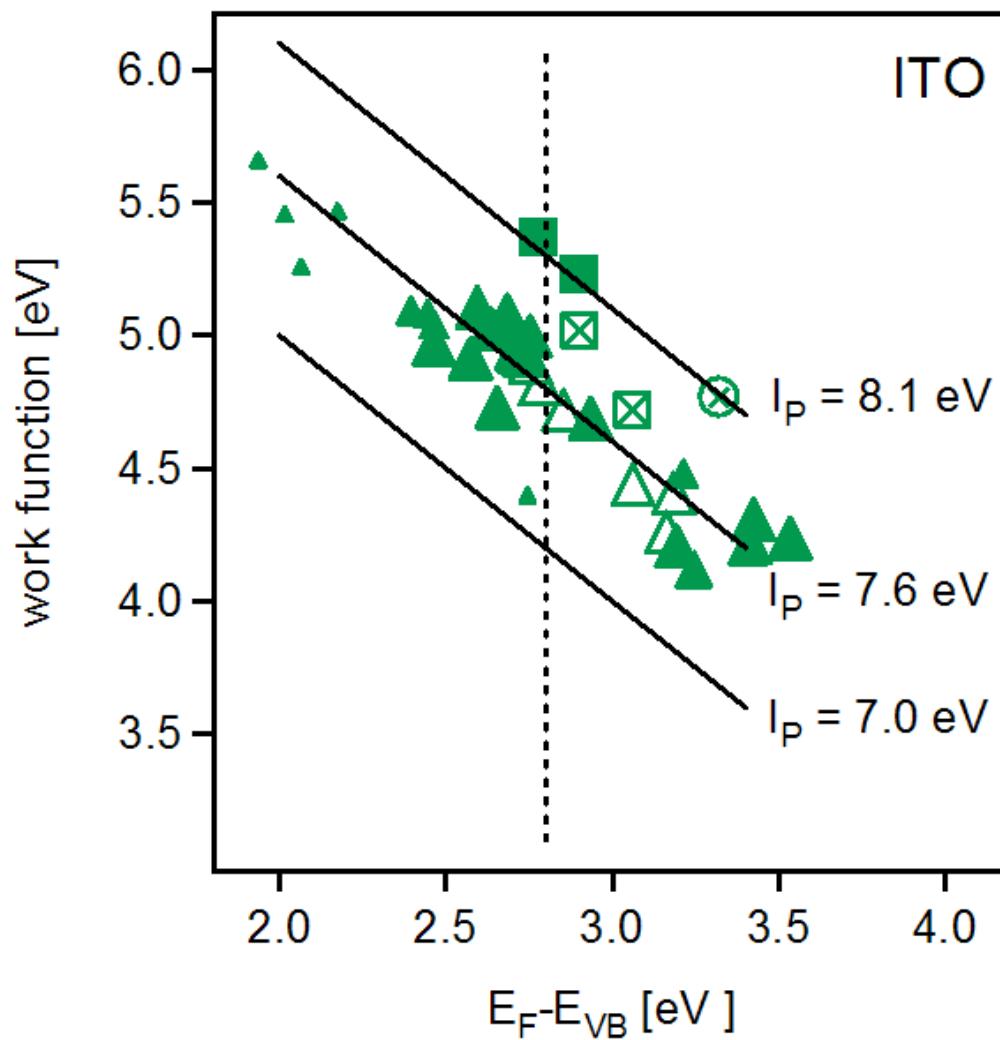


- Ionization potentials –
 - Vary little on (111) and (110) surfaces
 - Vary greatly on (100) surface
 - Metallic termination = low ionization potential
 - Oxide termination = high ionization potential

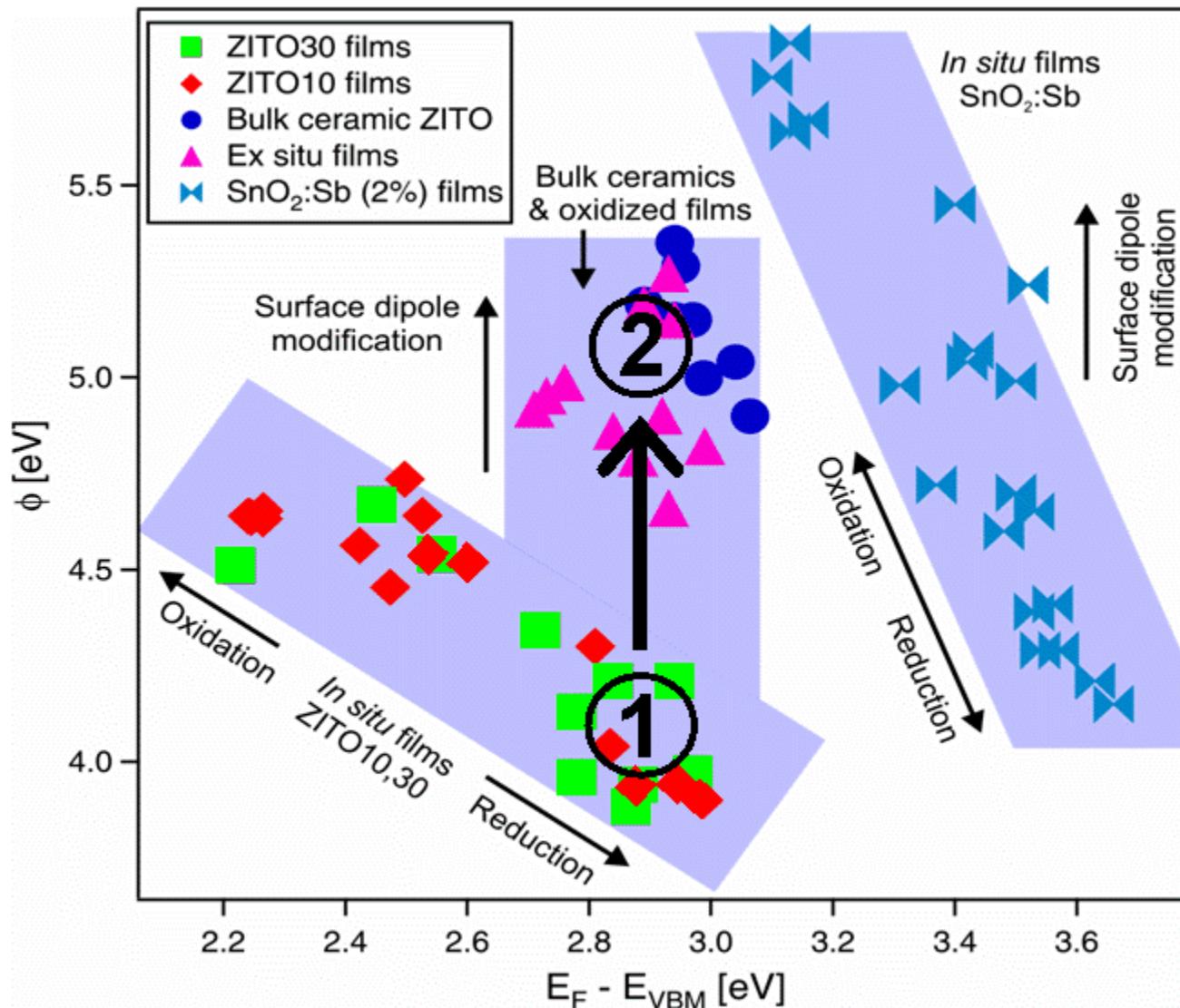
In_2O_3 Surfaces



ITO Surfaces

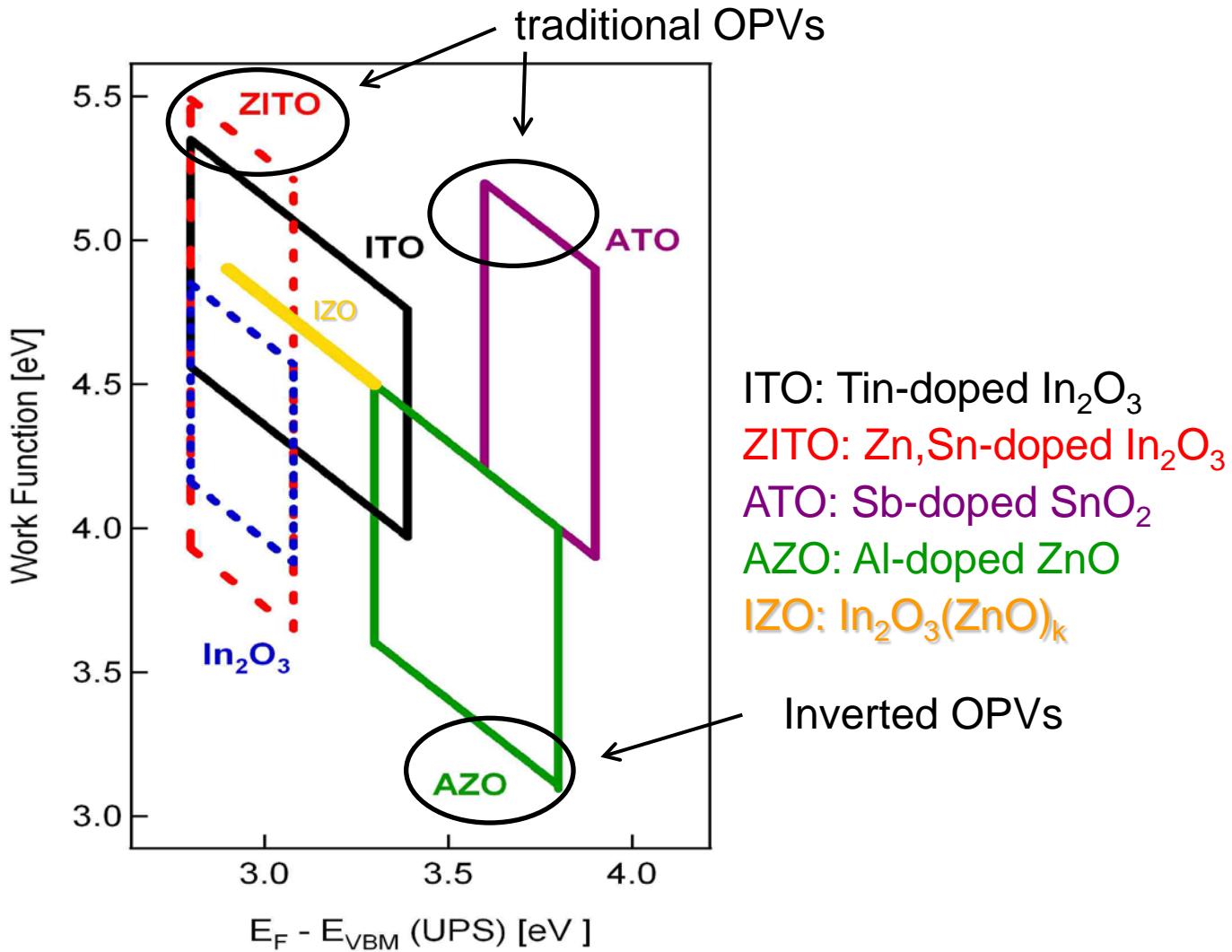


Two-Step Processing



Parallelogram Plots

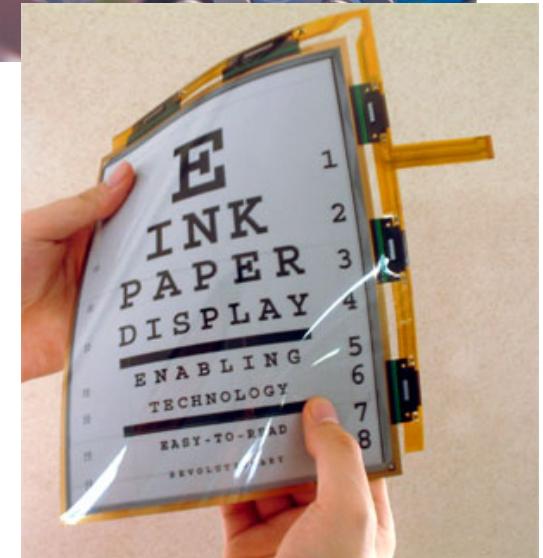
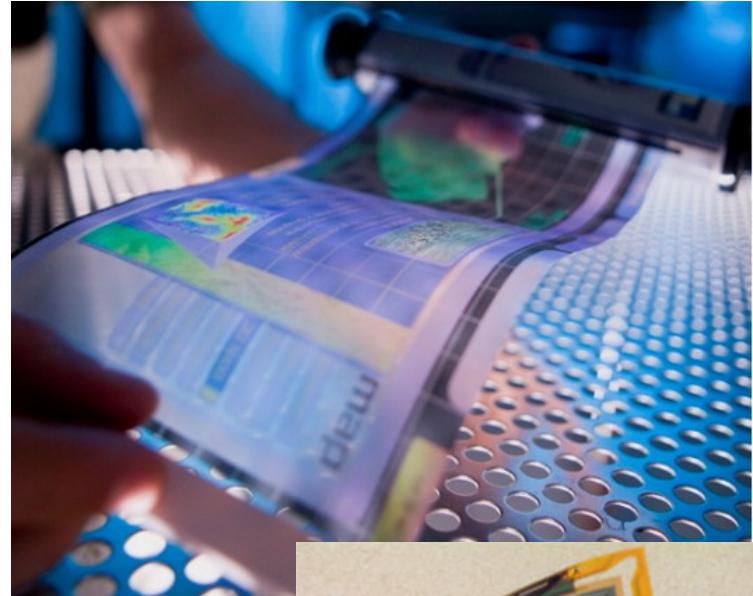
- Left side:
Fundamental
Band-gap
- Right side:
maximum
Burstein-Moss shift
- Top and bottom:
achievable ionization
potential ranges



Amorphous TCOs

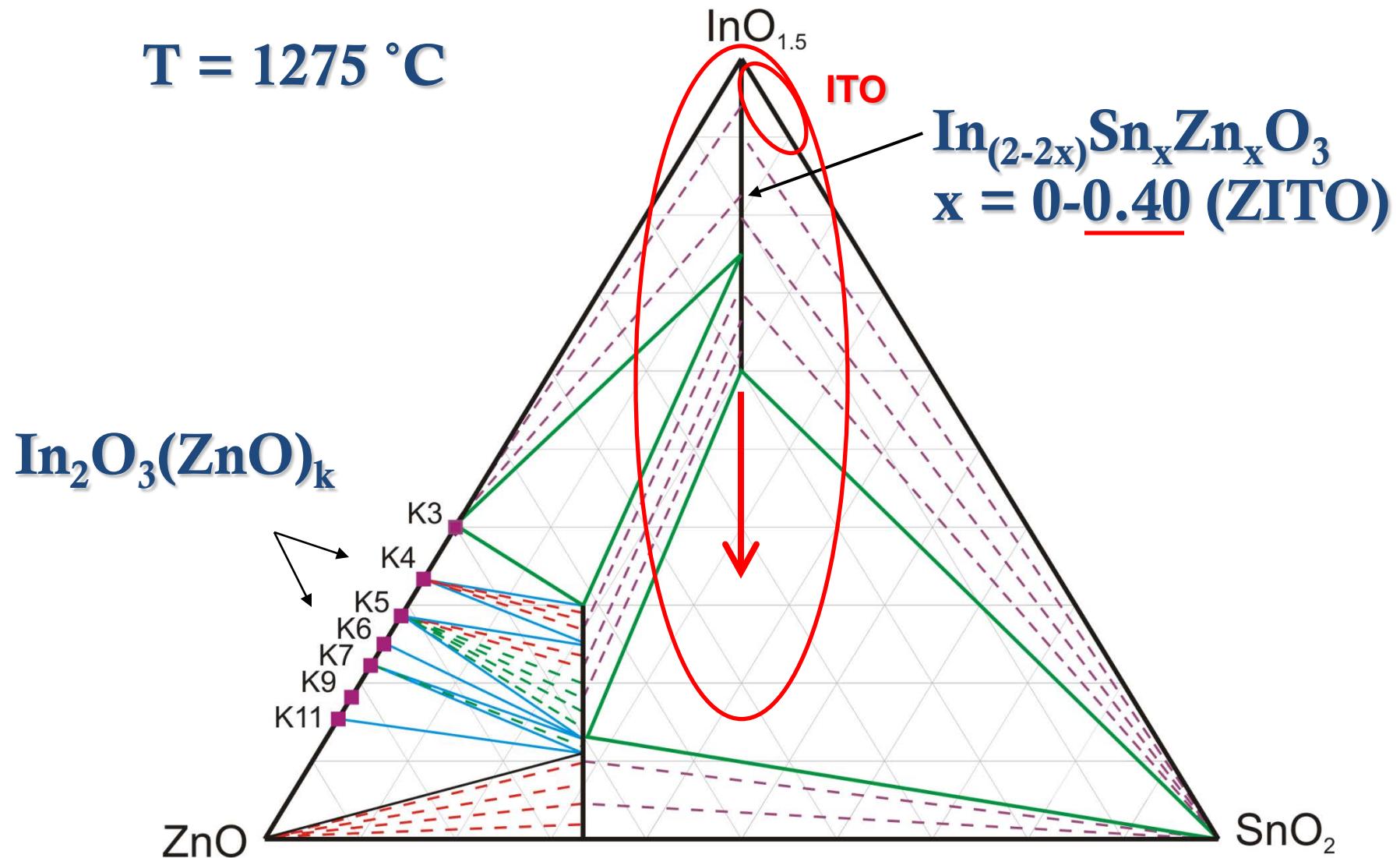
Advantages of Amorphous TCOs

- Easier, cheaper processing
 - Low temperature
 - Flexible substrates
 - Better etching characteristics
- Smoother surfaces
- Wide composition range
 - Minimization of toxic/expensive elements
- No hot/cold spots



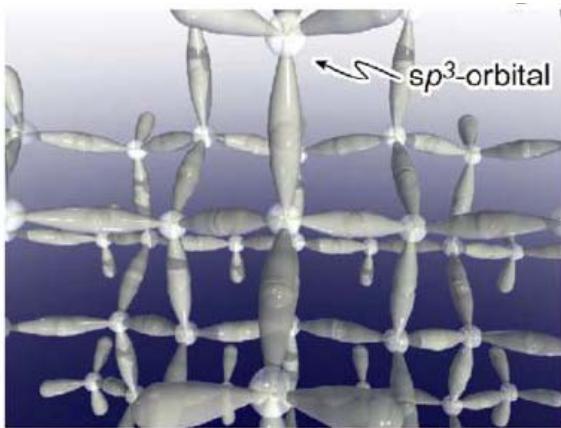
Amorphous ZITO TCOs

T = 1275 °C

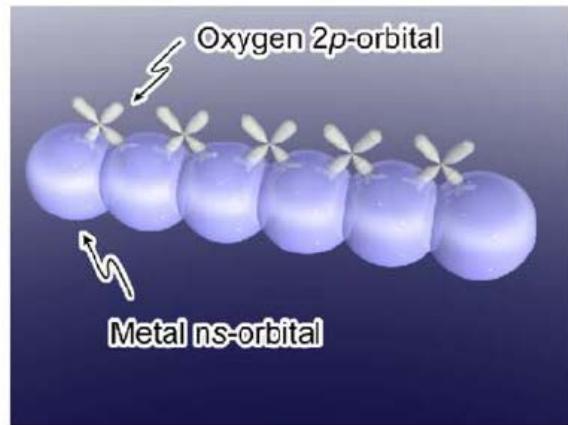


Why a-TCOs Have Good Properties

Conventional Semiconductor
(silicon)

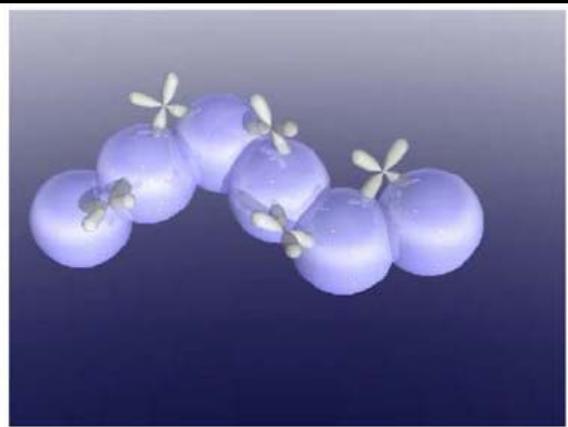
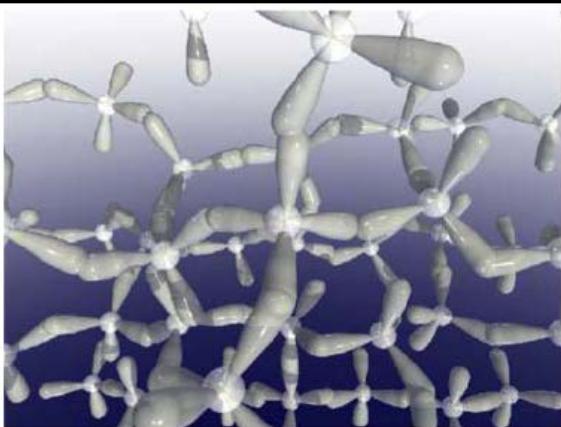


Traditional TCO
(indium oxide)

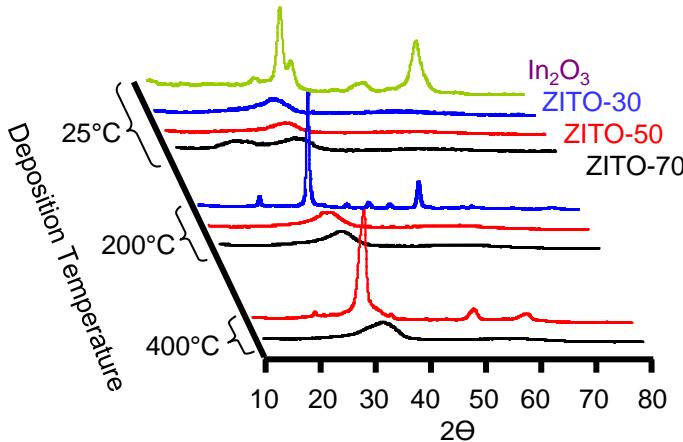


Crystalline

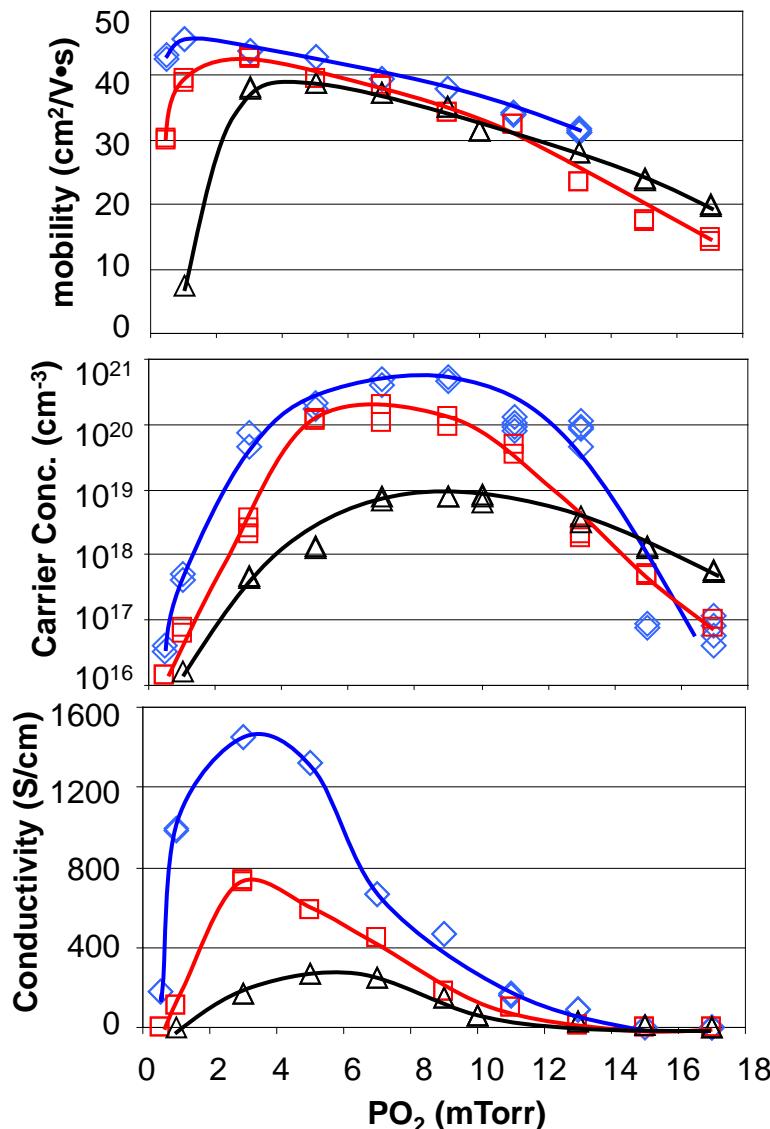
Amorphous



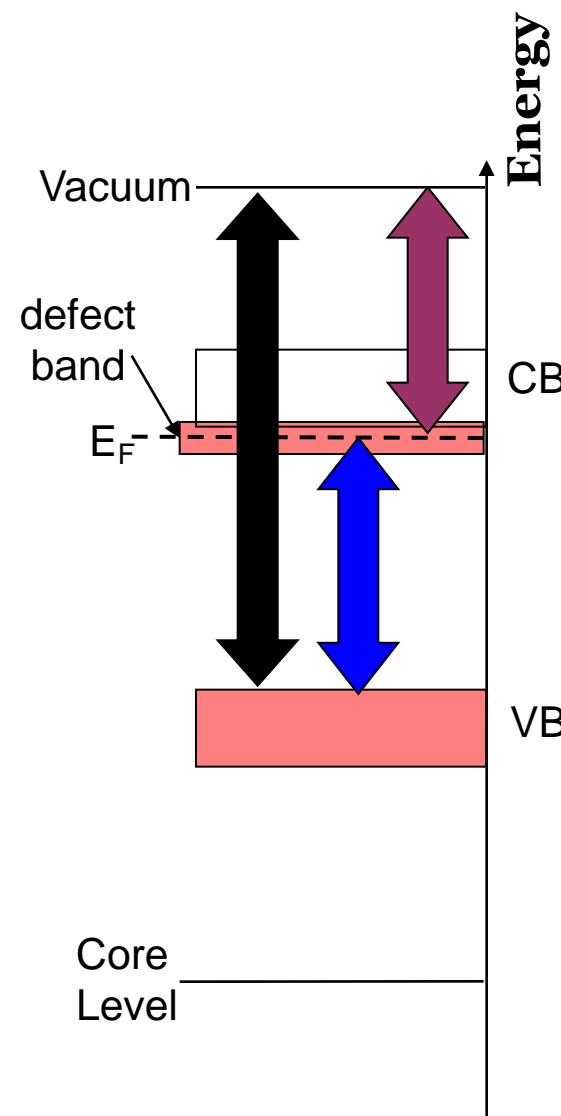
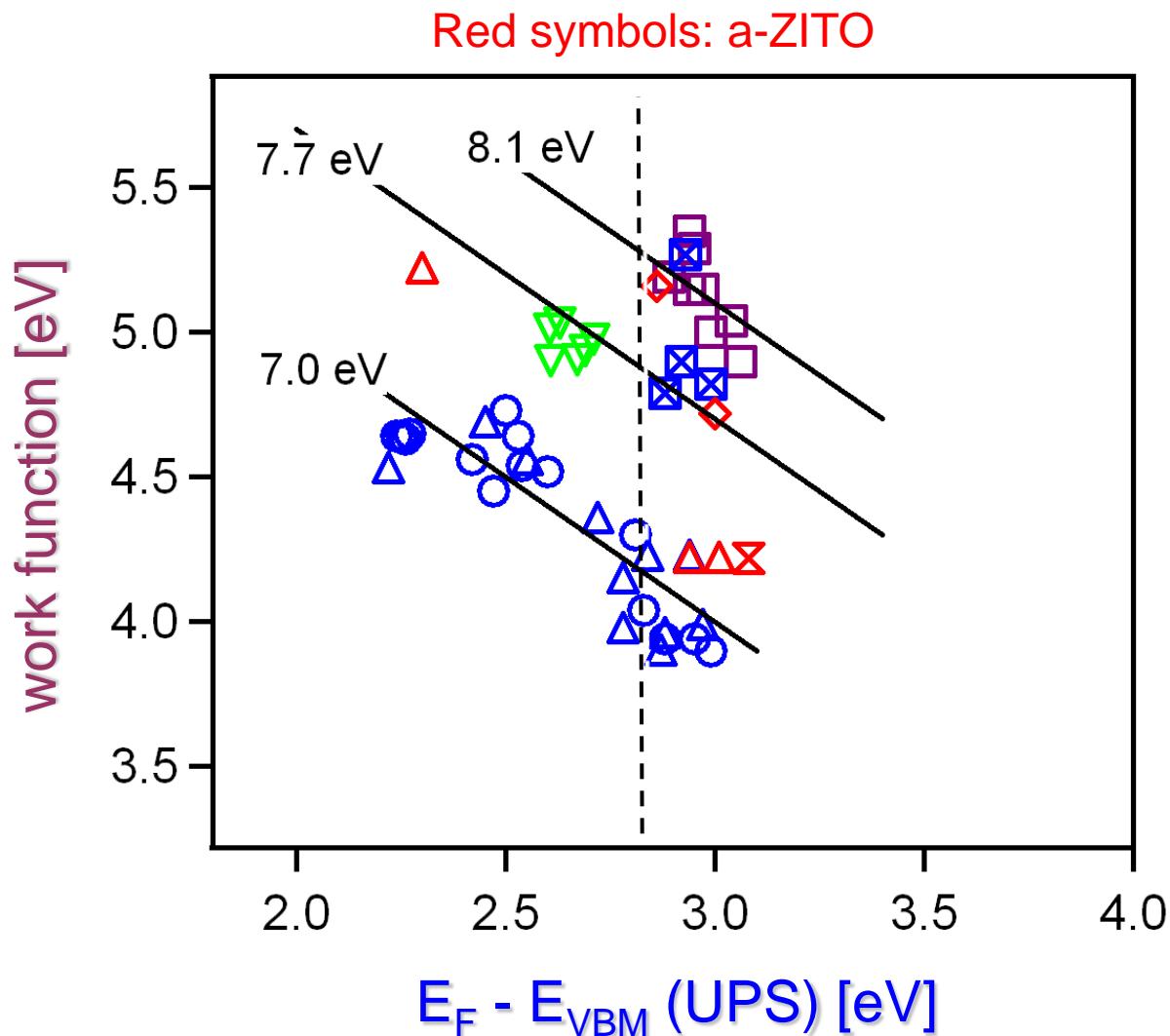
Pulsed Laser Deposited a-ZITO Films



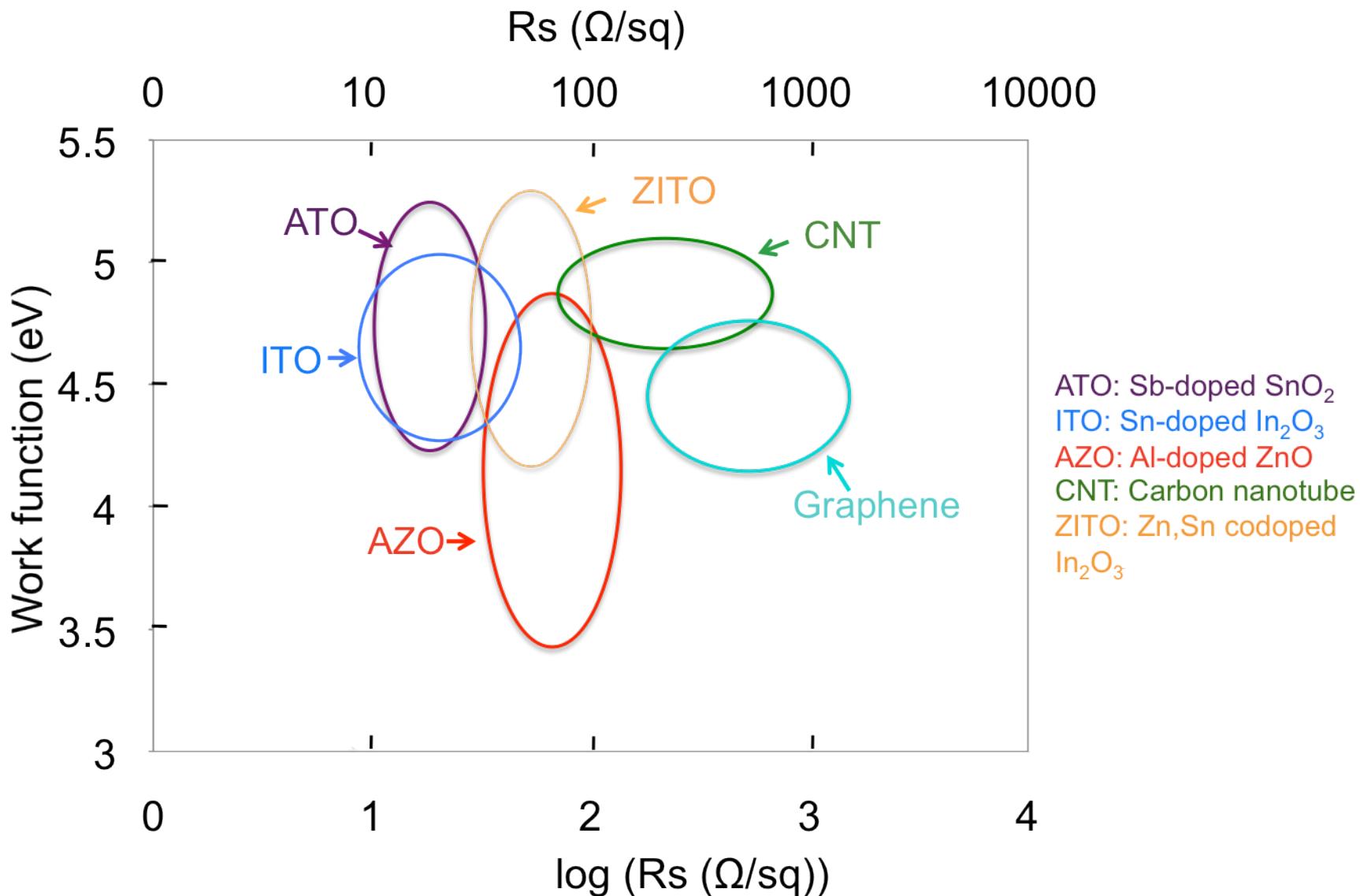
In₂O₃: No cosubstitution
ZITO-30: 30 at.% cosubstituted
ZITO-50: 50 at.% cosubstituted
ZITO-70: 70 at.% cosubstituted



How a-ZITO Compares

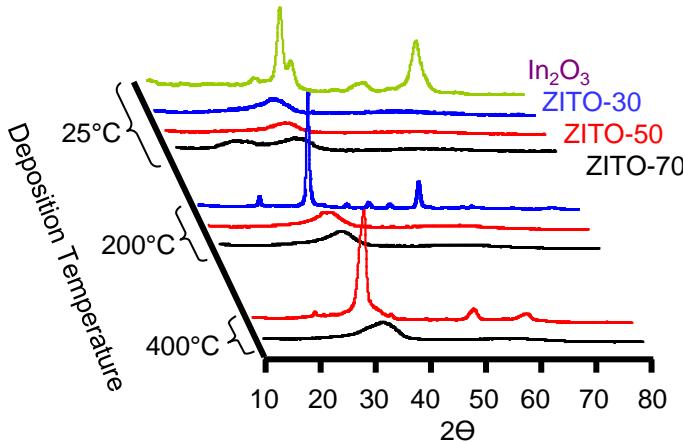


Ashby Plot of TCO Properties

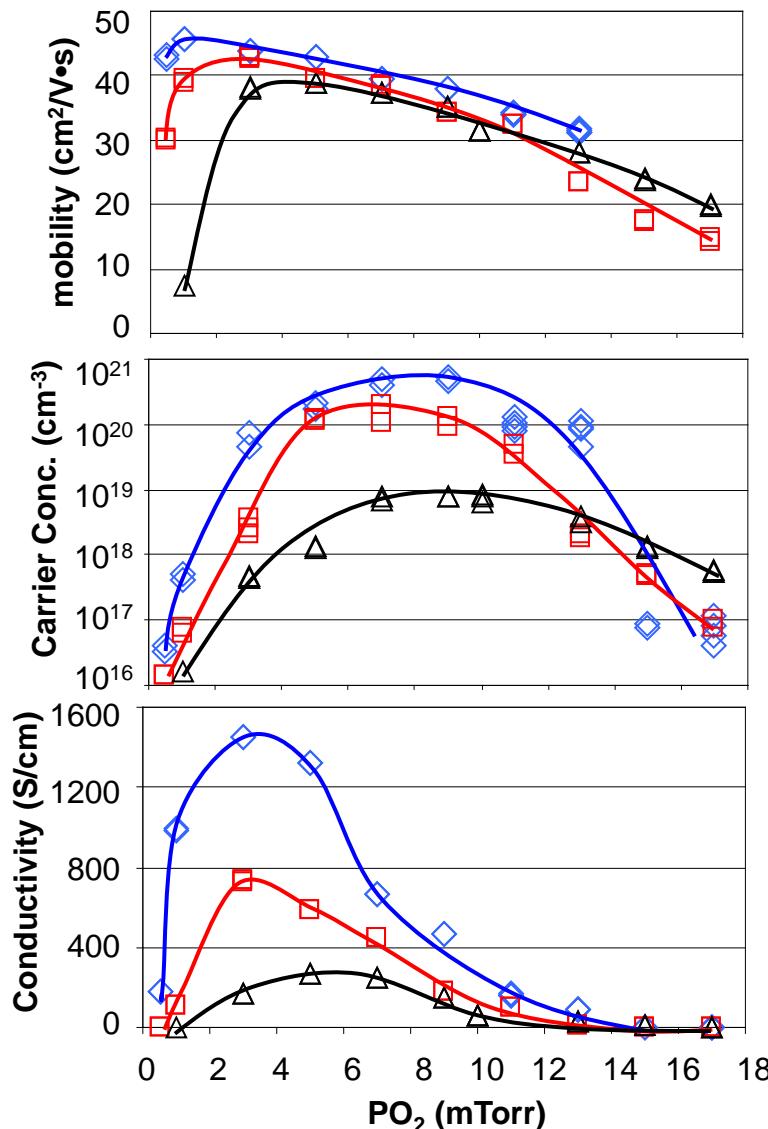


What the Future Holds

Pulsed Laser Deposited a-ZITO Films

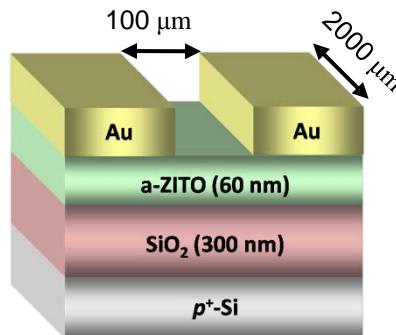


In₂O₃: No cosubstitution
ZITO-30: 30 at.% cosubstituted
ZITO-50: 50 at.% cosubstituted
ZITO-70: 70 at.% cosubstituted



Application of ZITO TCO & TOS for FETs

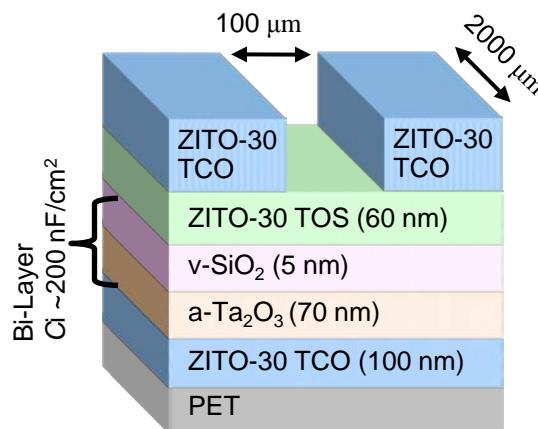
TOS ZITO-30 used for Field Effect Transistor (FET) Channel Layer



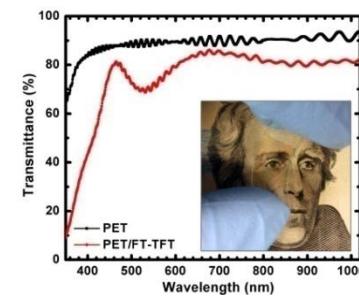
C_i for 300 nm SiO₂: ~10 nF/cm²
 V_G and V_{DS} : ~100 V
 μ_{FE} : ~10 cm²/V·s
 I_{on}/I_{off} : ~10⁶
 V_T : ~18 V
SS: ~5.2 V/decade
Air and light stable

TCO ZITO-30 used for Gate, Source & Drain
TOS ZITO-30 used for Channel Layer

On plastic substrate to form all amorphous, flexible, transparent FET



V_G and V_{DS} ~4.0 V
 μ_{FE} ~20 cm²/V·s
 I_{on}/I_{off} ~10⁵
 V_T ~ 1.2 V
SS ~0.26 V/decade
Good Mechanic Flexibility
Transparency ~75%



ZITO Films Grown at Room Temperature by PLD

Conclusions

- TCO work functions can be modified “intrinsically” through:
 - Fermi level shifts (via donor doping—defect chemistry plays a vital role!)
 - Surface dipole modifications by:
 - Changing surface orientations (e.g., Al-doped ZnO)
 - Altering surface terminations (e.g., Sb-doped SnO₂)
 - By changing surface stoichiometry (e.g., peroxidation, Sn-doped In₂O₃ or ITO, Zn,Sn-cosubstituted In₂O₃ or ZITO)

Conclusions (cont'd)

- Work function vs. Fermi level “parallelogram plots” allow comparison of candidate TCOs for OPV applications
 - AZO (Al-doped ZnO) or alternatives (Ga-doped ZnO) are best for low work function applications, e.g., in inverted OPV designs
 - ZITO (Zn-In-Sn-O) or ATO (Sb-doped SnO₂) and alternatives (FTO, F-doped SnO₂) are best for high work function applications, e.g., in traditional OPV designs
- Amorphous TCOs exhibit work functions and Fermi levels comparable to their crystalline counterparts (e.g., ZITO)
- An emerging “frontier” for TCOs is as Amorphous Oxide Semiconductors (AOSS)